SPACE USER'S MANUAL

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1. Introduction

1.1 What is Space

Space is an advanced layout to circuit extractor for analog and digital integrated circuits. From a mask-level layout, *space* produces a circuit netlist. This netlist contains

- active devices,
- instances of other cells (only in hierarchical mode),
- terminals (if they are defined in the layout).

Optionally, this netlist contains

- wiring capacitances to substrate,
- inter-wire coupling capacitances (both cross-over coupling capacitances and lateral coupling capacitances),
- wiring resistances,
- substrate resistances and capacitances.

These parasitics are extracted very accurately, this is a must for state-of-the-art IC technologies where interconnection parasitics tend to determine maximum circuit performance.

Besides accuracy, another key characteristic of *space* is efficiency. This is mainly due to new algorithms for handling the IC geometry and careful implementation of the program. *Space* is intended for on-line, interactive use but without problems it handles very large designs even on a workstation or on a minicomputer.

Space can operate in hierarchical mode (in which case the extracted circuit possesses the same hierarchical structure as the layout from which it is derived), in flat mode (in which case only one circuit cell is generated for the total layout), or in mixed flat/hierarchical mode.

1.2 Benefits of Using Space

A layout as extracted by *space* can be simulated while fully taking into account all parasitic elements. This is important, since the decrease of feature sizes and the increase of chip dimensions make the influence of wiring parasitics on the performance of the chip critical, or even dominant: Gate delays decrease but wiring delays may actually increase.

Since *space* is an integrated on-line tool, and very fast, the effects of wiring parasitics can be taken into account in the *design loop*. This prevents

- missed performance targets or even malfunction of the silicon produced,
- and/or costly redesigns when the problem is detected late (when relying on stand-alone verification tools).

Space enables meaningful performance/functional characterization, even for submicron technologies, early in the design process.

1.3 Features

The main features of *space* are summarized as below. Space is ...

- **hierarchical**
- **capable of extracting 45 degree polygonal layout**
- **extremely fast**
  The running time is linear in the size of the layout. The extraction speed is depending on the extraction options selected.
- **technology independent**
  Space is capable of extracting parasitics from analog and digital, MOS and bipolar layouts. *Space* accepts user defined/adjusted element definition files.
- **needs little computer memory**
  The memory usage is slightly worse than proportional to the square-root of the size of the layout. Consequently, *space* can extract huge flat layouts using a minimum amount of memory.
- **accurately extracts lateral and crossover coupling capacitances**
  The capacitance model employed by *space* includes surface to surface, edge to surface and edge to edge coupling capacitances.
- **extracts bipolar device model parameters**
  Bipolar device model parameters are extracted using layout information like emitter area, emitter perimeter and base width.
- **employs Finite Element methods for accurate resistance extraction**
  These are much more accurate than polygon-partitioning based heuristics, and nearly as efficient.
- **produces accurate but simple RC networks**
  Space employs a new, Elmore time constant preserving algorithm to transform a detailed Finite Element RC mesh into a low complexity lumped network that accurately models the distributed nature of the parasitic resistance and capacitance of IC interconnects. To model higher order time constants, the number of RC sections in the output network is a function of the maximum signal frequency which can be adjusted by the user.

- **can extract substrate resistances and capacitances**
  In order to model substrate coupling effects in analog and mixed digital/analog circuits, *space* can apply an accurate numerical technique or a fast interpolation technique to extract the substrate resistances. Additional, substrate capacitances can be extracted using the same accurate technique or fast by using a rc-ratio.
- **can read/write various layout/circuit formats**
  For example, CIF or GDSII input and SPICE, SPF, SPEF, EDIF or VHDL output.
- **enables trading of accuracy versus computer time**
  Users can select the type of parasitics they want to extract.

1.4 Documentation on Space

The following documentation on *space* is available:

- **Space User's Manual**
  This document. It is not an introduction to *space* for novice users, those are referred to the *Space Tutorial*.
- **Space Tutorial / Space Tutorial Helios Version**
  The space tutorial provides a hands-on introduction to using *space* and the auxiliary tools in the system that are used in conjunction with *space*. It contains several examples. The space tutorial helios version provides a similar hands-on introduction, but now from a point of view where the graphical user interface *helios* is used to invoke *space*.
- **Manual Pages**
  For *space* as well as for other tools that are used in conjunction with *space*, manual pages are available describing (the usage of) these programs. The manual pages are on-line available, as well as in printed form. The on-line information can be obtained using the *icdman* program.
- **Xspace User's Manual**
  This short manual describes the usage of *Xspace,* a graphical X Windows based interactive version of *space.* Note, however, that a more general graphical user interface to *space* is provided by the program *helios*.
- **Space 3D Capacitance Extraction User's Manual**
  The space 3D capacitance extraction user's manual provides information on how *space* can be used to extract accurate 3D capacitances.
- **Space Substrate Resistance Extraction User's Manual**
  This manual describes how resistances between substrate terminals are computed in order to model substrate coupling effects in analog and mixed digital/analog circuits.

2. Space Program Usage

2.1 Introduction

This chapter will describe *space*. Its many characteristic features are discussed in separate sections within this chapter. Each of the features is controlled by one or more of the following:

- **Command-Line Options**
  These are mainly flags that can be used to enable or disable some aspects of the extraction process or otherwise influence the behavior of *space*. For example, capacitance extraction is disabled by default, but can be turned on by using the **-c** option. Some options can also be specified in the parameter file. Options overrule specifications in the parameter file.
- **The Element Definition File**
  In this file, it is described how *space* can recognize the circuit elements (transistors, contacts, interconnects etc.) from the layout. This file also contains unit values for capacitances and resistances. By default, *space* reads this file from the appropriate directory of the ICD process library. See also Section 2.11 and Chapter 3.
- **The Parameter File**
  This file contains values for several variables that control the extraction process, like minimum values of resistances to be retained in the extracted netlist. Also this file is default read from the appropriate directory of the ICD process library. Some parameters can also be specified as options. Options overrule specifications in the parameter file. See also Section 2.12.

The relevant aspects of each of these control mechanisms are discussed in each section, and are summarized at the end of each section. An overview of all command-line options is given in appendix A.

2.2 General

2.2.1 Invocation and Basic Options

Space is normally invoked via the Unix command interpreter, or shell, as follows:

`space` *[options] cellname [cellname ...]*

The *cellname* arguments specify which layouts are to be extracted, at least one cellname has to be specified. The options influence the behavior of *space*, as will be shown in the rest of this chapter. A basic option is **-v**, which makes *space* prints some useful information during the extraction process.

2.2.2 Hierarchical and Flat Extraction

By default, *space* operates in **hierarchical mode**. In this mode, the circuit that is produced has the same hierarchical structure as the layout from which it is derived. *Space* will traverse the hierarchy itself, it is thus only necessary to specify the root(s) of the tree(s) to be extracted on the command line. To forbit traversal use option **-T**. Note that *space* does never extract imported sub-cells (cells of other projects).

Space operates in **flat mode** when using the **-F** option. In flat mode, the layout will be fully instantiated (flattened) before extraction and the circuit will have no sub-cells (except library and device cells, see *xcontrol(1ICD)*).

2.2.3 Mixed Flat/Hierarchical Extraction

In **hierarchical mode**, it is possible to perform a mixed flat/hierarchical extraction and by defining one or more layout cells to have the macro status using *xcontrol(1ICD)*.
In that case, in contrast to the instances of other cells, all instances of macro cells are flattened before extraction. When a macro cell has one or more child cells itself, the macro status of each of these child cells determines if the instances of these cells are also flattened. The use of macros may for example be advantageous when using small sub-cells for which it is cumbersome to define terminals (see Section 2.2.5), or when extracting sea-of-gates circuits, where the image is in a separate cell that is instantiated "under" all other cells.

In **flat mode**, it is also possible to perform a mixed flat/hierarchical extraction. This can be done by setting the library or device status for one or more sub-cells with *xcontrol*.
In that case, the layout of the whole circuit will be expanded, expect for the instances of library and device cells, which will be included as instances in the extracted netlist.

2.2.4 Incremental Operation

In **hierarchical mode**, *space* operates in *incremental mode* by default. In incremental mode, *space* does not extract sub-cells for which the circuit is up-to-date. *Space* uses an internal algorithm to select cells for (re-)extraction, as follows:

- extract all cells that have not yet been extracted,
- extract all cells of which the layout is newer than the extracted circuit,
- extract all cells that have one or more child cells of which the layout is newer than the extracted circuit,
- extract all cells that have one or more child cells for which the extraction status (see *xcontrol(1ICD)*) has been changed after the last extraction of the cell,
- extract cells that are at a depth <= *depth,* where *depth* is specified with the option **-D** *depth.* The root of the tree is at depth 1, its children are at depth 2, and so on. By default, *depth* = 1, so cells that are are given as argument with *space* are always extracted.

Incremental mode is disabled completely with the **-I** option. In this non-incremental mode, all cells in the tree are extracted. (Note that this option is equal to specifying a large number for *depth*.) The options **-I** and **-D** are useful when changing extraction style, e.g. to extract all cells with coupling capacitances if they were done with substrate capacitances only.

2.2.5 Terminals

An electrical network or circuit as extracted by *space*, is built up from primitive elements (transistors, capacitors and resistors), subcircuits (when the input layout is hierarchical) and terminals. *Terminals* (sometimes also called *ports* or *pins*) are connectors to the outside world and are used for building up the hierarchical structure of the circuit. The extracted netlist specifies the connectivity among all these elements.

For *space* to be able to produce these terminals in the extracted circuit, the input layout must also have terminals. Layout terminals are named rectangular areas or points (this is dependent on how they are specified in the layout input file or using the layout editor) in an interconnect layer of the layout. *Space* uses the terminals in the layout to create, name and connect the terminals in the circuit according to a one-to-one correspondence between layout terminals and circuit terminals. Terminal names must be unique within a cell.

For flat extraction, only the topmost cell must have terminals. For hierarchical extraction, the topmost cell and all the other cells in the hierarchy must have terminals, unless the cell is used as a macro (see Section 2.2.3). *Space* identifies a connection from a cell being extracted (the parent cell) to a sub-cell (or child cell) when a layout feature of the parent cell touches or overlaps a terminal of the child cell. *Space* identifies a connection between two sub-cells when a terminal of one sub-cell touches or overlaps a terminal of another sub-cell.

> **NOTE:**
> If a sub-cell does not have terminals, set the macro status for the sub-cell, or use flat extraction only.

In case of hierarchical extraction (without setting the macro status), *space* would not detect such connections. In fact, *space* would be unable to represent those non-hierarchical connections in a hierarchical circuit netlist. The program will not give a warning in case of such non-hierarchical connections.

> **NOTE:**
> If a sub-cell has terminals but the sub-cell is connected via layout polygons of the sub-cell that are only extensions the real terminal areas of the sub-cell, set the interface type for the sub-cell to free (or freemasks) (using *xcontrol(1ICD)*) or use flat extraction only.

By setting the interface type for the sub-cell to free (or freemasks), the layout of the sub-cell will be expanded in the father cell (with freemasks only for certain masks) and the

sub-cell will be appropriately connected via its terminals. Note, however, that other elements may then also be recognized in the parent cell (see also Section 2.9).

2.2.6 Limitations of Hierarchical Extraction

Hierarchical extraction is also impossible (in the sense that it results in an incorrect circuit) if the functionality of the child cells is modified by layout features in the parent cells. For example, a polysilicon feature in a parent cell that overlaps an active area feature in a child cell modifies the circuit of the child cell by creating a transistor in it. Flat extraction is not a problem in this case and will result in a correct circuit.

While flat extraction is necessary in some cases as mentioned above, it is recommended when it is required to get the highest accuracy of the parasitics extracted. One reason for this is the fact that (parasitic) coupling capacitances between layout features of different cells don't fit in a hierarchical circuit description. However, flat extraction is often not a significant burden because *space* is very fast. Also, the extracted circuit is often used for simulation and most simulators must flatten the circuit anyway, since internally they only can work on a flattened netlist.

Appendix B gives some guidelines for how to construct a layout such that a hierarchical extraction by *space* will suffer least from these difficulties and hence is more accurate.

2.2.7 Command-Line Options

-v	Set verbose mode.
-F	Set flat extraction mode, i.e. produce a flattened netlist.
-T	In hierarchical mode, only extract the top cell(s).
-I	Unset incremental (hierarchical) mode: do not skip sub-cells for which the circuit is up-to-date (*depth* = ∞).
-D *depth*	Selectively unset incremental (hierarchical) mode for all cells at level <= *depth* (default *depth* = 1).
-u	Do not automatically run the preprocessors *makeboxl(1ICD)* and *makegln(1ICD).*

2.2.8 Parameter File

When the parameter *flat_extraction* is specified in the parameter file, a flat extraction is performed.

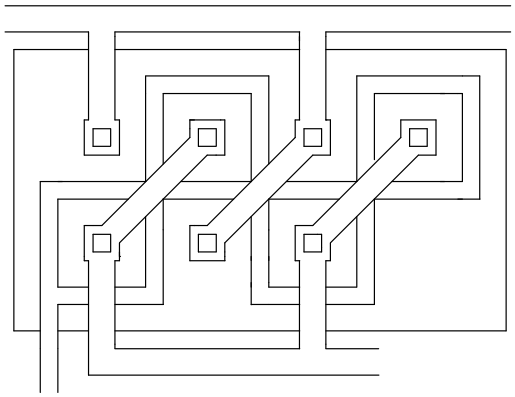
parameter	type	unit	default	suggestion
flat_extraction	boolean	-	off	-

2.3 Extraction of Field-effect Transistors

Space recognizes field-effect transistors (e.g. MOS transistor) from the different mask combinations in the layout (see Section 3.4). The extractor will calculate the width and length of each field-effect transistor. For that matter, *space* uses perimeter and surface formulas, as described below. When the **-t** option is used, the position of each transistor is specified in the extraction output.

2.3.1 Drain-source connections

For each field-effect transistor *space* will extract one gate connection, optionally a bulk connection, and one drain/source connection for each set of drain/source areas that are connected. As an example, for the following layout of a transistor (which has 5 drain/source areas, divided into 2 different sets), *space* will extract one gate connection, possibly a bulk connection (if this connection is specified in the element definition file), one drain connection and one source connection.



If a field-effect transistor is used as a capacitor and has only one connected set of drain/source areas, two connections will be generated that are however attached to the same net. If a field-effect transistor has more than two drain/source connections, only two of these connections appear in the extracted circuit. (These will in general be the connections that are connected to other parts of the circuit; dangling connections are not used in this case.)

2.3.2 Transistor width and length calculation

For each field-effect transistor, its width and length are calculated and stored in the attributes w and l. The transistor width and length are calculated from

$$length = \frac{per_g}{N_g}$$

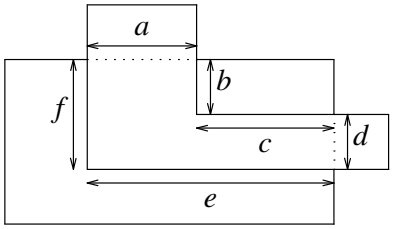
$$width = \frac{A}{length}$$

where

per_g is the part of the perimeter of the transistor where the gate extends the active area (see below),

N_g is the number of separate areas where this occurs, and

A is the total area of the transistor.



$$per_g = a + d$$

$$per_{tot} = a + b + c + d + e + f$$

If the transistor has no gate overlaps ($N_g = 0$) the width and length of the transistor are calculated from:

$$width = \frac{per_{tot}}{2}$$

$$length = \frac{A}{width}$$

where

per_{tot} is the total perimeter of the transistor.

2.3.3 Transistor drain/source parameters calculation

When a condition list for the drain/source region of the transistor is specified in the element definition file (see Section 3.4.9), and when capacitance extraction is enabled, the area, perimeter and number of equivalent squares for both drain and source region will be computed. In the perimeter of the drain and source, the edge that coincides with the transistor channel, is not included. When more than one transistor is connected to a drain/source region, the area value that is obtained for the total drain/source region is subdivided over the different transistors in proportion to the widths of the transistors. Apart from some constant that represents the length of the subdivided drain/source regions, the perimeter value is split in a similar way. The number of equivalent squares *nrx* for the drain/source region of a transistor is computed from:

$$nrx = \frac{ax}{width^2}$$

where *ax* is the area of the drain/source region and *width* is the width of the transistor.

2.3.4 Command-Line Options

Extraction of field-effect transistors is controlled by the following option:

-t Add positions of devices and sub-cells to the extracted circuit.

2.3.5 Element Definition File
See section 3.4.9 for the specification of the field-effect transistor elements.

2.4 Bipolar Device Extraction

Space recognizes bipolar junction transistors (BJT's) by combining semiconductor regions of type 'n' and 'p'. Bipolar junction transistors are divided into two groups: vertical and lateral transistors. For the vertical transistors, *space* calculates the emitter area and perimeter. They are stored in the attributes area and length, respectively. For the lateral transistors, the width of the base - the smallest distance between collector and emitter - is also calculated and stored in the attribute basew. For both groups, the **-t** option enables *space* to output the position of the emitter for each transistor.

2.4.1 Terminal connections
For each bipolar junction transistor, *space* will extract only one connection for each device terminal (collector, base, emitter and optionally a substrate terminal). Multi-emitter transistors are extracted as separate devices (one for each emitter). When a lateral transistor is recognized that has the same mask for both the emitter and the collector connections, it is assumed that the collector has the larger area.

2.4.2 Command-Line Options
Extraction of bipolar devices is controlled by the following option:

-t Add positions of devices and sub-cells to the extracted circuit.

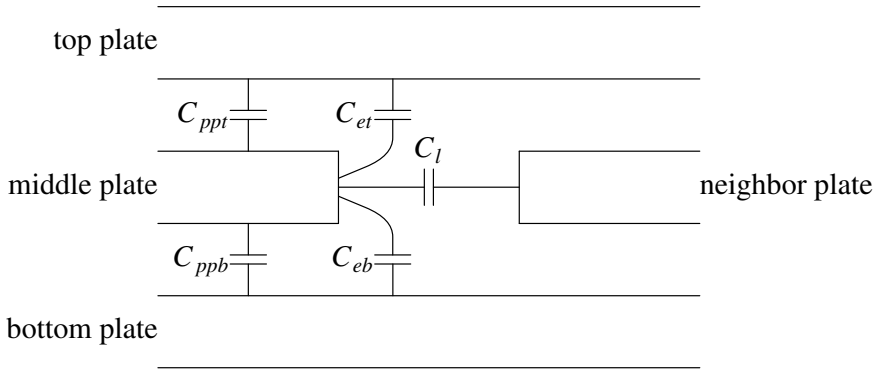
2.4.3 Parameter File
The following parameters for the parameter file control the extraction of bipolar transistors. The *lat_base_width* parameter defines the maximum base width that a lateral transistor can have. Lateral transistor configurations with a width larger than this value are not recognized as being transistors.

parameter	type	unit	default	suggestion
lat_base_width	real	micron	0	3

2.4.4 Element Definition File
See section 3.4.10 for the specification of the bipolar transistor elements.

2.5 Capacitance Extraction

2.5.1 Capacitance Definitions
Space uses an area/perimeter based capacitance extraction method. To describe the capacitance model employed by *space,* refer to the following figure and definitions:



Bottom plate	Lowest conductor, e.g. substrate, active area, polysilicon or first metal.
Top plate	Can for example be second metal, but can also be absent.
Middle plate	Can for example be polysilicon or first metal.
Neighbor plate	Not necessarily in same layer as middle plate.
C_{ppb}	Parallel-plate capacitance from middle-plate to bottom-plate. This can be a substrate capacitance or a cross-over coupling capacitance.
C_{ppt}	Parallel-plate capacitance from middle-plate to top-plate, this is a cross-over coupling capacitance.
C_{eb}	Edge capacitance of middle conductor to bottom conductor. This can be a substrate capacitance or a fringe-coupling capacitance.
C_{et}	Edge capacitance of middle conductor to top conductor. This is a fringe-coupling capacitance.
C_l	Lateral coupling capacitance between two parallel conductors.

2.5.2 Parallel Plate Capacitances

The parallel plate capacitances C_{ppt} and C_{ppb} between two wires that overlap over an area A are calculated from

$$C_{ppt} = c_{ppt}\ A$$

$$C_{ppb} = c_{ppb}\ A$$

where c_{ppt} and c_{ppb} are capacitances per square meter.

2.5.3 Lateral Coupling Capacitances

The value of a lateral coupling capacitance can be computed in two different ways, dependent on how the capacitance is specified in the element definition file.

One possibility is that a single value for the capacitance is specified in the element definition file. In that case, the lateral coupling capacitance between two parallel wires that are at a distance d over a length l is calculated from

$$C_l = c_l \frac{l}{d}$$

where c_l is the value that is specified in the element definition file (c_l corresponds to the capacitance for a configuration where the distance between both wires is equal to their length).

Another possibility, which allows to specify more accurate capacitance values, is that the the lateral coupling capacitance is specified as a function of different distances between the wires. In that case, the specification of the lateral capacitance has one or more (distance, capacitivity) pairs that each specify the capacitance between two parallel wires of a length of 1 meter for one particular distance between the wires. The lateral coupling capacitance for other configurations is found from an interpolation between two (distance, capacitivity) pairs. For the interpolation, the function

$$C_l = l \frac{a}{d^p}$$

is used if the capacitance for both adjacent points is larger than zero and $p \geq 1$, and

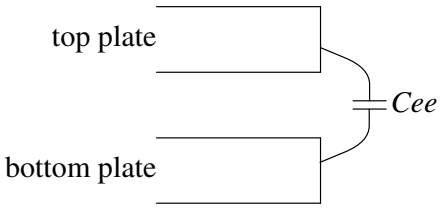
$$C_l = l \left(\frac{a}{d} + b\right)$$

is used otherwise. If the actual distance is larger or smaller than any specified distance, an extrapolation is done using the above functions.

Lateral coupling capacitance extraction is controlled by the *lat_cap_window* parameter from the parameter file. This parameter specifies in microns the distance over which lateral coupling capacitance is considered significant. When the wires are at a distance that is larger than *lat_cap_window,* no lateral coupling capacitance will be extracted for these wires.

2.5.4 Edge Capacitances

In addition to the edge-to-bottom capacitance C_{eb} and the edge-to-top capacitance C_{et}, also edge-to-edge capacitances between wires that are on top of each other can computed, as C_{ee} in the figure below.



One possibility to specify edge capacitance in the element definition file is by specifying a single value c_e which denotes the edge capacitance per meter edge length. The edge capacitance C_e between one wire that overlaps the edge of another wire over a length l, or between two wires of which the edges coincide over a length l, is then calculated from

$$C_e = c_e \; l$$

However, if also lateral coupling capacitances are extracted, these simple equations do not hold anymore, as the values of C_{eb}, C_{et} and C_{ee} are effected by the lateral capacitances. *Space* offers two ways of dealing with this, either by using an heuristical method, or by allowing the user to specify explicitly how large the edge capacitances become if other conductors are nearby.

The heuristical method uses the fact that experiments show that for conductors that are not too narrow and/or too close to other conductors, the sum of the ground capacitances and the coupling capacitances that are connected to that conductor is approximately constant. Therefore, for each conductor edge to which a lateral coupling capacitance is connected, *space* tries to keep the sum of the ground capacitance and the coupling capacitances constant by decreasing the value of the other (non-lateral) edge capacitances that are connected to that edge. This is achieved by subtracting from each non-lateral edge capacitance C_{ex} (where C_{ex} is C_{et}, C_{eb} or C_{ee}) that is connected to the edge, a value $minimum\ \{C_{ex}, \frac{C_{ex}\ C_l\ compensate\_lat\_part}{C_{ex-all}}\}$, where C_{ex-all} is the sum of all connected non-lateral edge capacitances and *compensate_lat_part* is a parameter. Note that this parameter has a default value 1 (for full compensation). But if you want to have no full compensation, set the value of parameter *compensate_lat_part* smaller than 1.

The second way of dealing with the effect of lateral coupling on the edge capacitances, is by explicitly specifying in the element definition file (distance, capacitivity) pairs, similar to the possibility used for lateral coupling capacitances (see previous section). (Note, to use this second way, parameter *compensate_lat_part* must be greater than 0.) Each pair gives the edge capacitance per meter edge length for given distance to a neighboring conductor that is of the same type (e.g. both wires are of type metal1). If $(d_{\max}, c_e)$ is the pair with maximal specified distance (and therefore also maximal edge capacitance), $C_e = c_e \; l$ for all distances larger than $d_{\max}$ or for a situation where no neighboring wire of the same type is present. The edge capacitance for other configurations is found from an interpolation between two (distance, capacitivity) pairs. The following interpolation

function is used:

$$C_e = c_e\ (1 - b \exp(-p\ d))\ l$$

If the actual distance is smaller than any specified distance, the same formula is used, with b fixed at 1. These formulas apply both for C_{eb}, C_{et} and C_{ee}. Edge capacitances that are explicitly specified as a function of the distance to neighbor wires, are not affected by the first method.

2.5.5 Coupling Capacitances When Extracting Only Substrate/Ground Capacitances
When only substrate/ground capacitances are extracted and no coupling capacitances (the option **-c** is used and the option **-C** and **-l** are not used), all non-lateral coupling capacitances that are specified in the element definition file are added as ground capacitances to the two wires to which the coupling capacitance is connected.

2.5.6 Extracting Capacitances of Different Types
For each capacitance that is extracted it is possible to specify its type (see Section 3.4.13). Unlike parallel capacitances that are of a same type, parallel capacitances of a different type are not joined during extraction.

2.5.7 Extracting Junction Capacitances
Default, junction capacitances (see Section 3.4.13) will be extracted as linear capacitances.

If the parameter *jun_caps* is set to "non-linear" the extracted capacitance will be of the specified type.

If the parameter *jun_caps* is set to "area" the extracted capacitance will be of the specified type and, moreover, the value of the extracted capacitance will specify the area of the element (if only an area capacitivity is specified for that capacitance type) or the edge length of the element (if only edge capacitivity is specified for that capacitance type). If *jun_caps* is set to "area", and both area capacitivity and edge capacitivity are specified for one junction type, the value of the extracted capacitance will be equal to the extracted capacitance value divided by the area capacitivity (so in this case, effectively, the total vertical and horizontal junction area is extracted).

If the parameter *jun_caps* is set to "area-perimeter" the extracted capacitance will be of the specified type and the area and perimeter of the element will be represented by the instance parameters *area* and *perim* in the database. See section 4.2 for then how to convert these parameter names to the parameter names that are appropriate for the simulator that is used.

If the parameter *jun_caps* is set to "separate" the extracted capacitance will be of the specified type and the area and perimeter of each capacitance that is specified in the capacitance list for that type will separatedly be represented with parameters *area*<*nr*> and *perim*<*nr*> where <*nr*> denotes that it is the <*nr*>-th. area or the <*nr*>-th. perimeter element in the list. This may e.g. be useful when it is required that for one junction

capacitance element the perimeter adjacent to the gate oxide and the perimeter adjacent to the field oxide are specified as separate parameters. (See again section 4.2 for how to convert the parameter names to the parameter names that are appropriate for the simulator that is used.)

Note that junction capacitances of drain/source areas can also be extracted as drain/source area and perimeter information attached to the MOS transistors, see Section 3.4.9.

2.5.8 Name of Ground or Substrate Node

Ground or substrate capacitances are on one side connected to a node that is called "GND" (if @gnd is used as terminal mask in the element definition file) or "SUBSTR" (if @sub is used as terminal mask in the element definition file), see Section 3.4.13. These names can be changed using respectively the *name_ground* parameter and the *name_substrate* parameter from the parameter file.

2.5.9 Command-Line Options

Capacitance extraction is controlled by the following options:

-c Extract capacitances to substrate/ground.

-C Extract coupling capacitances as well as capacitances to substrate. This option implies **-c**.

-l Also extract lateral coupling capacitances, implies **-C**.

2.5.10 Parameter File

The following parameter for the parameter file controls the extraction of capacitances.

parameter	type	unit	default	suggestion
lat_cap_window	real	micron	0	3-5
compensate_lat_part	real	-	1	1
jun_caps	string	-	linear	area-perimeter
name_ground	string	-	GND	-
name_substrate	string	-	SUBSTR	-

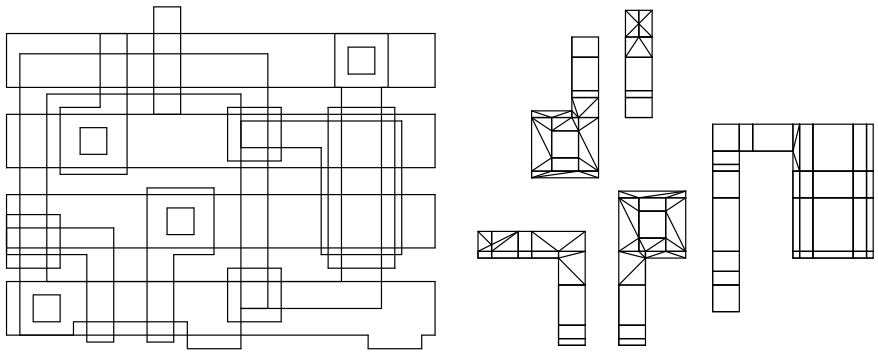
2.5.11 Element Definition File

See section 3.4.13 for the specification of the unit capacitance values (i.e. c_{ppt}, c_{ppb}, c_{et}, c_{eb} and c_l) for the different interconnection layers.

2.6 Resistance Extraction

2.6.1 General

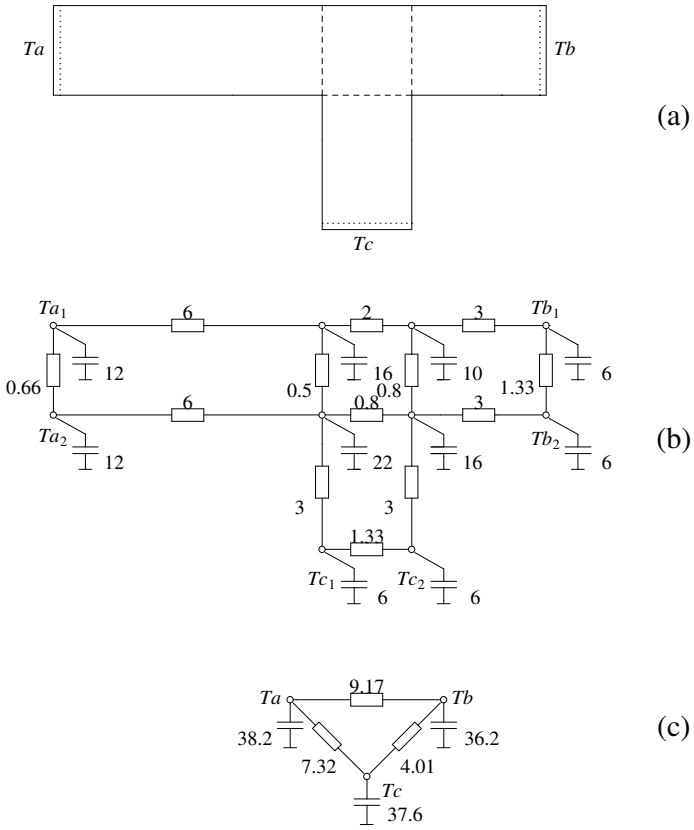
When extracting resistances, *space* applies finite element techniques to construct a fine resistance mesh that models resistive effects in detail. An example of a layout and the finite element mesh produced for the polysilicon mask is in the figure below:



The finite element mesh is equivalent to a detailed resistance network and *space* initially constructs this detailed resistance network to model the resistances. Then it applies a Gaussian elimination (or, equivalently, a star-triangle transformation) node reduction technique to simplify the network and to find the final resistances. The final network will in general contain (1) the nodes that are terminals, (2) the nodes that are labels, (3) the nodes that are transistor connections (gate, source, drain, emitter etc.), (4) the nodes that are introduced by the algorithm in Section 2.7, (5) the nodes that are connected to resistances of different types, (6) - if metal resistances are not extracted or when equi-potential lines are detected (see Section 2.8.1 and Section 2.8.11) - the nodes that correspond to equi-potential regions, and (7) - if substrate resistances are extracted (see the Space Substrate Resistance Extraction User's Manual) - the nodes that represent substrate terminals. This is described in more detail in Section 2.8.

When extracting resistances together with capacitances, the extractor will add lumped capacitances to the nodes of the initial resistance network to model the distributed capacitive effects. In that case, the node reduction will proceed such that the Elmore time constants between the nodes in the final network are unchanged with respect to their value in the fine RC mesh. This will guarantee that the electrical transfer function of the final network closely matches that of the fine RC mesh and, consequently, that of the actual circuit.

The extraction of resistances together with (ground) capacitances is illustrated below. In (a) it is shown how a T shaped interconnection with terminals *Ta*, *Tb* and *Tc* is subdivided into finite elements, which are all rectangles in this case. In (b) the RC network is shown that models the resistive and capacitive effects in detail. In (c) the final network is shown that is obtained after eliminating the internal nodes and collapsing the nodes that belong to the same terminal.



2.6.2 Improved Accuracy

By default, *space* uses a rather coarse finite element mesh to compute resistances. The accuracy of the resistances as obtained with this mesh may not always be sufficient. In particular, obtuse triangles in the mesh may be generated that have a bad influence on the accuracy of the method and that produce negative resistances in the detailed resistance network. Under some circumstances, negative resistances (and negative capacitances as a by-product of the network reduction heuristics) may also appear in the final network.

To obtain an improved accuracy with resistance extraction, the option **-z**, may be used. On the penalty of a somewhat longer extraction time, this option generates a finer finite-element mesh that contains (almost) no obtuse triangles. As a result, more accurate resistance values are found and negative resistances do not occur in the output network.

When using the option **-z**, the parameter *max_obtuse* specifies the maximum (obtuse) angle of a corner of a triangle of the finite element mesh. A smaller value for *max_obtuse* (use $90 \leq max\_obtuse \leq 180$) results in a finer finite element mesh, but also in longer extraction times.

NOTE:
The usage of the option **-z** may result in large finite element meshes, and hence long extraction times, when resistances are extracted for large rectangular areas like e.g. wells.

2.6.3 Extracting Resistances of Different Types

For each conductor it is possible to specify the type of the resistance that is extracted (see Section 3.4.8 and Section 3.4.12). Parallel resistances of different types will not be joined during extraction. Neither will nodes be eliminated that are connected to resistances of different types.

2.6.4 Selective Resistance Extraction

Selective resistance extraction is possible by specifying interconnects in a file called 'sel_con' and by using either the option **-k** or **-j**. When using the option **-k**, resistances will only be extracted for the interconnects that are specified in the file 'sel_con'. When using the option **-j**, resistances will be extracted for all interconnects except for the interconnects that are specified in the file 'sel_con'. The format of the file 'sel_con' is as follows. On each line, an x position, an y position and a maskname is specified. When an interconnect has the specified mask on the specified layout position, that interconnect is specified in the file.

2.6.5 Contact Resistances

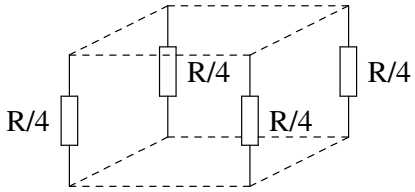
When extracting resistances, with each contact area a resistance is associated that has a value

$$R = \frac{r}{A}$$

where

r is the contact resistance in ohm square meter, and
A is the area of the contact.

The contact resistance R is subdivided over the corners of the contact as shown in the figure below.



The top plane and bottom plane (in dashed lines) represent the two layers that are connected by the contact, which on their turn may also be represented by resistors if resistances are extracted for these layers. The value of r should be tuned to give accurate results for typical size contacts.

2.6.6 Elimination Order

To reduce memory usage, *space* creates the detailed RC mesh while scanning the layout from left to right. It eliminates each internal node as soon as this is possible, i.e. as soon as all network elements that are connected to the node are known. However, this strategy will in general result in an elimination order that is not optimal with respect to computation time. Since the cost of each elimination is proportional to the square of the number resistances that are connected to the node, it is often more efficient to first eliminate the node that has the lowest number of resistances connected it, then the node that has - after the previous operation - the lowest number of resistances connected to it, etc.. To allow *space* to select for elimination a node with a low number resistances connected to it, a buffer can be defined in which the nodes are temporarily stored that are ready for elimination. When the buffer becomes full, the node with lowest degree is selected for elimination and it is removed from the buffer. The size of the buffer is defined using the parameter *max_delayed.* A large value of *max_delayed* may result in significantly faster extraction times, but a too large value of *max_delayed* will also result in large memory usage. A large value for *max_delayed* will in general be useful for circuits that contain large rectangular area for which resistances are extracted such as n-wells.

2.6.7 Command-Line Options

Resistance extraction is controlled by the following options:

-r Extract resistances for high-resistivity (non-metal) interconnect.

-z Apply mesh refinement for resistance extraction (implies **-r**).

-k Selective resistance extraction, resistances are only extracted for specified interconnects.

-j Selective resistance extraction, resistances are extracted for all but specified interconnects.

The threshold value to determine whether an interconnect is high-resistive or low-resistive is specified by the parameter *low_sheet_res* in the parameter file (default, *low_sheet_res* = 1 ohm per square).

2.6.8 Parameter File

Resistance extraction is controlled by the following parameters from the the parameter file:

parameter	type	unit	default	suggestion
max_obtuse	real	degree	90.0	110.0
low_sheet_res	real	ohm	1.0	1.0
low_contact_res	real	ohm.m2	0.1e-12	0.1e-12
max_delayed	integer	-	100000	500-200000

2.6.9 Element Definition File

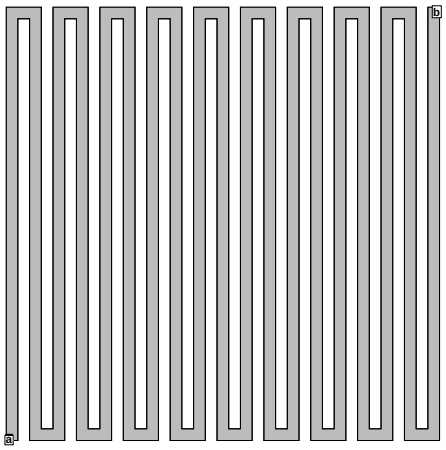
See section 3.4.8 for the specification of the sheet resistance values for the interconnection layers, and see section 3.4.12 for the specification of the contact resistances.

2.7 Frequency Dependent Number of RC Sections

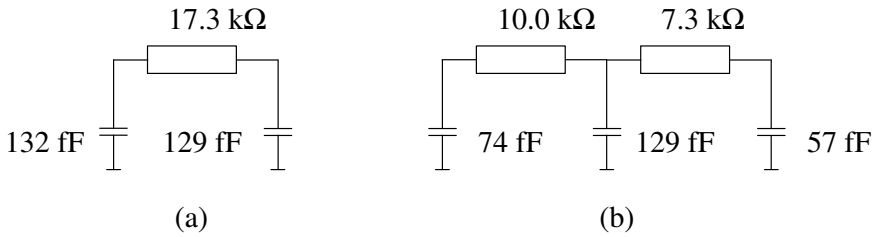
In some occasions (for high frequencies) the RC network that is extracted for the interconnections may contain too few elements to allow a simulation of the extracted circuit afterwards with sufficient accuracy. For example, if an interconnection has two terminals, the extractor will extract an RC network consisting of one resistor and two capacitors (one π-section), while an accurate simulation of the interconnection may require at least two π-sections. In that case, the option **-G** may be used. This option causes that, instead of eliminating *all* the internal nodes in the initial RC mesh (see Section 2.6.1), a Selective Node Elimination (SNE) is performed in which, besides the nodes that are normally retained in the extracted network (terminals, transistor connections, etc; see Section 2.6.1), also other nodes are retained.

When using the the option **-G**, a parameter *sne.frequency* has to be specified in the parameter file that specifies the maximum signal frequency that occurs in the extracted circuit. The complexity of the extracted network will be a function of the parameter *sne.frequency.* The higher the value of *sne.frequency* the more nodes will be retained in the final network, such that the reduced network accurately models the detailed network (i.e. the network before reduction). If *sne.frequency* ≤ 0, no additional nodes are retained.

As an example we consider the spiral resistor that is shown below.



The RC network that is default extracted for it is shown below in (a). When using the option **-G** and when using for parameter *sne.frequency* the value 50e9, one non-terminal node of the initial RC mesh will be retained in the final RC network and the RC network as shown in (b) is obtained.



2.7.1 Command-Line Options

More detailed RC network extraction is controlled by the following option:

-G Extract RC models that are accurate up to a certain frequency.

2.7.2 Parameter File

More detailed RC network extraction is controlled by the following parameter from the the parameter file:

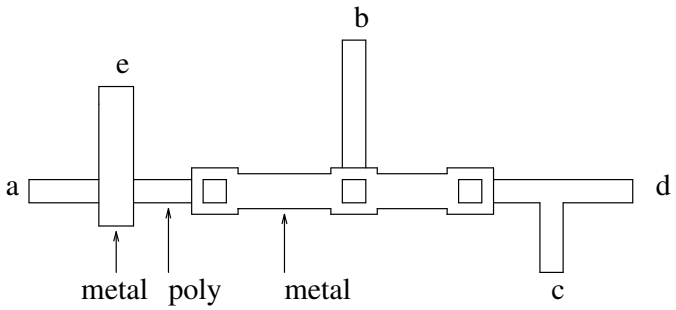
parameter	type	unit	default	suggestion
sne.frequency	real	Hz	1e9	1e9

2.8 Network Reduction Heuristics

When extracting resistances and capacitances, *space* can apply some heuristics to further reduce the number of elements (resistors, capacitors and nodes) in the final network by neglecting irrelevant detail. These heuristics include

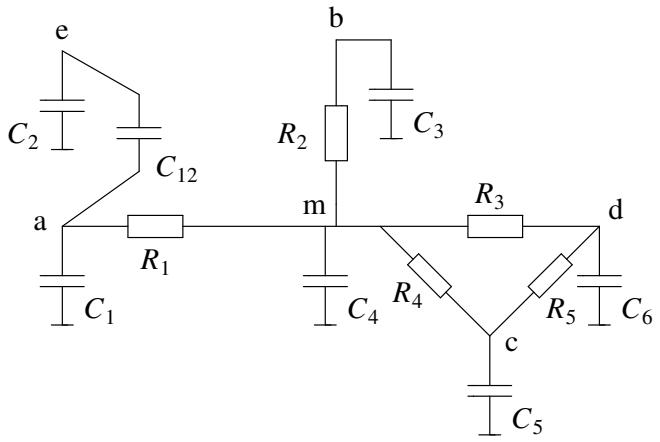
- Retaining of nodes corresponding to equi-potential regions (i.e. pieces of interconnect for which no resistance is extracted) in order to prevent the creation of complete resistance graphs on the terminal nodes of large conductors (e.g. power and ground lines, clock lines and large busses with many connections).
- Merging of (terminal) nodes that are connected by a small resistance.
- Removal of large resistances that are shunted by a low resistivity path.
- Reconnecting small coupling capacitances to ground.

Below, we will introduce these heuristics, and for illustration we use the following layout:



In general, after Gaussian elimination but before applying the network reduction heuristics, the network will contain (1) the nodes that are terminals, (2) the nodes that are labels, (3) the nodes that are transistor connections (gate, source, drain, emitter etc.), (4) the nodes that are introduced by the algorithm in Section 2.7, (5) the nodes that are connected to resistances of different types, (6) - if metal resistances are not extracted or when equi-potential lines are detected (see Section 2.8.1 and Section 2.8.11) - the nodes that correspond to equi-potential regions, and (7) - if substrate resistances are extracted (see the Space Substrate Resistance Extraction User's Manual) - the nodes that represent substrate terminals.

For the above example, when assuming that non-metal resistances and ground and coupling capacitances are extracted, and when assuming that a, b, c, d and e are either terminals or gate, drain or source connections, the network that is initially extracted will have the following form:



In the above figure, node m corresponds to the piece of metal that connects the three different poly branches. If also metal resistances are extracted, or if no network reduction heuristics are applied, this node will not be present.

2.8.1 min_art_degree and min_degree heuristic

The *articulation degree* of a node is defined as the number of pieces in which the resistance graph would break if the node and its connected resistances were removed. Nodes that correspond to pieces of metal for which no resistances are extracted (e.g. node m in the last figure) will often have an articulation degree > 1. If a node has an articulation degree < *min_art_degree* and if (1) the node has no terminals or transistors connected to it, (2) the node has not been introduced by the algorithm in Section 2.7, (3) the node is not connected to resistances of different types, and (4) the node does not represent a substrate terminal (see the Space Substrate Resistance Extraction User's Manual), the node will be eliminated. If an equi-potential node has an articulation degree >= *min_art_degree,* or if it does not satisfy one of the 4 above conditions, the node will be retained in the final network.

The *degree* of a node is equal to the number of resistances connected to the node. Nodes with a degree >= *min_degree* and an articulation degree > 1 will also be retained in the final network.

> **Example:**
> Node m is not eliminated if its articulation degree (3 in this case) is more than or equal to *min_art_degree,* or if its articulation degree is more than one and its degree (4 in this case) is more than or equal to *min_degree.* Otherwise, the node is eliminated.

N.B. To find the articulation degree of a node, the extractor does not take into account interconnection loops.

2.8.2 min_res heuristic

This heuristic deletes small resistances from the network via Gaussian elimination of one of the nodes that is connected to the resistance. If a resistor has an absolute value that is less than the *min_res* parameter, and if the resistor is connected to a node that (1) is not connected to resistances of different types, and (2) does not have an articulation degree >= *min_art_degree,* or a degree >= *min_degree* (see the previous paragraph), the resistance is deleted by the elimination of that node. Terminals and transistor connections of the node that is eliminated are added to the other node that is connected to the resistor. The deletion is done incrementally: each time when one or more node have been eliminated, the network is checked again to see if new small resistances have arisen.

> **Example:**
> The resistors R_1, R_2, R_3, R_4 and R_5 are evaluated to see if their value is less than *min_res.* If this is true then one of the nodes to which the resistor is connected to is eliminated (not node m if this node was retained because of its degree or articulation degree) and its terminal label(s) and/or transistor connections are attached to the other node. The new network is again verified to see if there are any resistors that are smaller than *min_res,* etc.

2.8.3 min_sep_res heuristic
This heuristic deletes small resistances from the network by joining the two nodes that are connected by the resistance. If two nodes are connected by a resistor that has an absolute value that is less than *min_sep_res,* the resistor is deleted and the two nodes are merged. Note that while the *min_res* heuristic does not affect the total resistance between the remaining nodes, this heuristic, in general, does.

2.8.4 max_par_res heuristic
This heuristic prevents the occurrence of high-ohmic shunt paths between two nodes. If the ratio of the absolute value of a resistor and its minimum parallel resistance path (along positive resistors) exceeds the value of the *max_par_res* parameter, then the resistor is simply removed.

> **Example:**
> Assume $R_3 > 0$, $R_4 > 0$ and $R_5 > 0$. First it is checked if R_3 / (R_4 + R_5) > *max_par_res.* If this is true then R_3 will be removed. If this is not true then it is checked if R_4 / (R_3 + R_5) > *max_par_res.* If this is true then R_4 will be removed. If this is not true then it is checked if R_5 / (R_3 + R_4) > *max_par_res.* If this is true then R_5 will be removed. Recall that the elimination order is arbitrary.

2.8.5 no_neg_res heuristic
If the *no_neg_res* heuristic is on, all negative resistances will be removed from the network.

2.8.6 min_coup_cap heuristic
If, for both nodes a coupling capacitance is connected to, it holds that the ratio between the absolute value of the coupling capacitance and the value of the ground/substrate capacitance of the same type of that node, is less than the *min_coup_cap* parameter, then the value of the coupling capacitance is added to the ground capacitances of the two nodes and the coupling capacitance is removed.

> **Example:**
> If C_{12} / C_1 < *min_coup_cap* and C_{12} / C_2 < *min_coup_cap* then C_{12} is removed and its value is added to both C_1 and C_2.

2.8.7 min_ground_cap heuristic
If the absolute value of a ground/substrate capacitance is less than the *min_ground_cap* parameter, the ground/substrate capacitance is removed.

2.8.8 no_neg_cap heuristic
If the *no_neg_cap* heuristic is on, all negative capacitances will be removed from the network.

2.8.9 frag_coup_cap heuristic
In contrast to the other heuristics, this heuristic is applied during Gaussian elimination (see Section 2.6.1). When eliminating a node and redistributing a coupling capacitance that is connected to that node over the nodes that are adjacent, this heuristic decides

whether or not the adjacent node receives (a part of) the coupling capacitance. When *Rmin* is the minimum of the absolute values of the resistances that are connected to the node that is eliminated, and when *R* is the value of the resistance between the node that is eliminated and an adjacent node, then the adjacent node receives (a part of) the coupling capacitance if and only if $Rmin / |R| \geq frag\_coup\_cap$. Hence, a lower value of *frag_coup_cap* will give more detail in the extracted network, but it will also result in longer extraction times. For the fastest and least accurate form of resistance and coupling capacitance extraction, set *frag_coup_cap* equal to 1.

2.8.10 min_coup_area, min_ground_area and frag_coup_area heuristics

These heuristics are similar to their equivalences for capacitance (*min_coup_cap, min_ground_cap* and *frag_coup_cap*), but are used instead when junction capacitances are extracted as area and perimeter elements (see Section 2.5.7). They only look at the value of the area parameter(s) of the elements, not at the value of the perimeter parameter(s).

2.8.11 equi_line_ratio heuristic

If, during resistance extraction, for a rectangular piece of interconnect, the ratio length/width is more than *equi_line_ratio,* an equi-potential line is generated for that piece of interconnect. The equi-potential line is placed at the middle of the rectangle, perpendicular to the current flow. This will introduce an extra equi-potential node that is treated similarly as the nodes that are introduced by not extracting metal resistances (see Section 2.8.1). In general, this will simplify the extracted network and reduce extraction time. Especially when metal resistances are extracted, the reduction in network complexity and extraction time can be large. Currently, equi-potential lines are not detected for all interconnect rectangles.

2.8.12 keep_nodes

It is possible to keep nodes of certain capacitance (and contact) elements in the extracted network (these nodes are not eliminated). You need to specify a string of element names after the *keep_nodes* parameter. When you only want to keep one of the nodes of an element, you must add '.1' or '.2' to the element name. See for element names and the pin order the technology file.

Example:
keep_nodes lcap_cms ecap_cms_cpg.2

2.8.13 Parameter File

The heuristics are controlled by the following parameters from the parameter file:

parameter	type	unit	default	suggestion
min_art_degree	integer	—	+∞	3
min_degree	integer	—	+∞	4
min_res	real	ohm	0	100
min_sep_res	real	ohm	0	10
max_par_res	real	—	+∞	25
no_neg_res	boolean	—	off	on
min_coup_cap	real	—	−∞	0.04
min_ground_cap	real	farad	0	1e-15
no_neg_cap	boolean	—	off	on
frag_coup_cap	real	—	0	0.2
min_coup_area	real	—	−∞	0.04
min_ground_area	real	farad	0	1e-11
frag_coup_area	real	—	0	0.2
equi_line_ratio	real	—	+∞	1.0
keep_nodes	string	—	—	—

2.8.14 Command-Line Options

The following command-line option controls the heuristics:

-n Do not apply the circuit reduction heuristics.

2.9 Library Cell Circuit Extraction

When extracting a circuit that contains library cells (standard cells, gate arrays) the library cells themselves often need not to be extracted, but only the interconnects between the library cells. To let *space* perform an extraction in this way, set the extraction status for each library cell to "library" using the program *xcontrol(1ICD).* When a cell has a library status, *space* will not extract this cell, but it will include it as an instance in the extracted circuit, no matter whether hierarchical extraction is used or flat extraction.

The description of the library cell itself can be added to the database using a netlist conversion tool like *cspice(1ICD)* or *csls(1ICD).* When, however, instead of a netlist description, a model description needs to be specified for the library cell, set the extraction status for that cell to "device" using *xcontrol(1ICD)* and specify the model in the control file of the netlist retrieving tool (see Section 4) or use the tool *putdevmod(1ICD)* to specify the device model.

Sometimes it may be necessary to expand (parts of) the library cell in the parent cell. This may for example be the case when the cell connects to the father cell via other layout polygons than its terminal areas, or when the cell has feed-throughs that occur via

other layout polygons than its terminal areas. In that case, set the interface type for the cell to free (or freemasks) using the command *xcontrol(1ICD)*. This way, the contents of a library cell (for freemasks only certain masks) will be expanded its parent cell. Note, however, that capacitances etc. inside the cell will then also be extracted. If this is not desired (because the capacitances have already been accounted for in the description that is available for the library cell), one can use the following strategy: Add a dummy mask to the library cell and modify the element definition file that is used for extraction such that capacitances are only recognized for positions where the dummy mask is not present.

To prevent the replication of data, it is useful to store the library cells in a separate project and next import this project in the project where the design is present.

2.10 Back Annotation

2.10.1 Instance names

An instance name for a layout cell can be specified using a layout import tool (e.g. *cgi*) or using the layout editor *dali*. The corresponding instance in the extracted circuit will have the same name. If an instance in an extracted circuit is obtained from more than one level down in the hierarchy of that cell (e.g. in case the instances that contain the relevant instance are expanded in the top-level cell), the name of that instance is obtained by concatenating the names of all the different instances that contain the instance. The different instance names in this case are separated by a character that is specified by the parameter *hier_name_sep* (default the character '.'). If no instance name is specified in the layout, or if a hierarchical instance name can not be constructed because one of the instance names is missing, the instance name in the extracted circuit will be generated by the network retrieving tool that is used.

The instance names of elements that are recognized from the mask layout combinations (transistors, resistors, capacitors etc.) are generated by the extraction program or by the network retrieving tool that is used.

2.10.2 Net names

A net in the extracted circuit represents one conductor or (defined from a layout point of view) one set of electrically connected polygons. If no resistances are extracted, a net is represented in the circuit by exactly one node. If resistances are extracted, a net may be represented in the circuit by more than one node.

The name of a net, among other things, may be used to determine the names of the nodes that are part of the net (see Section 2.10.4). The specification of a net name can be done as follows:

- By defining a label for the net. The definition of a label requires the specification of a name, a mask, an x, y position and (optionally) a class. The name of the label is then used as the name for the net that is represented by the specified mask at the specified position. If more than one label is attached to a net, the net receives the name of the

label that has the smallest x coordinate or (if both x coordinates are equal) the smallest y coordinate. Labels may be defined as follows:

— Using the layout editor *dali* in the annotate menu.

— Using the program *cgi.*

If the parameter *no_labels* is set, the labels that are defined for a cell will not be used by the extractor.

- By setting the parameter *term_is_netname.* This will cause that each terminal of the cell (hence, not a terminal of a sub-cell !) is also interpreted as a label. Again, if more than one label is attached to a net, the net receives the name of the terminal that has the smallest x coordinate or (if both x coordinates are equal) the smallest y coordinate.
- By the use of inherited labels. Inherited labels originate from labels and terminals that are defined in sub-cells:

  If the parameter *hier_labels* is set, a label will be inherited from each label of a sub-cell that is flattened in the extracted cell.

  If the parameter *hier_terminals* is set, a label will be inherited from each terminal of a sub-cell that is flattened in the extracted cell.

  If the parameter *leaf_terminals* is set, a label will be inherited from each terminal of a sub-cell that is *not* flattened in the extracted cell.

  In each of the three above cases, the name of the inherited label is given by concatenating the names of all the different instances that contain the original label or terminal plus the name of the label or terminal itself. The different instance names are separated by a character that is specified by the parameter *hier_name_sep* (default the character '.'). The instance name(s) and the label or terminal name are separated by a character that is specified by the parameter *inst_term_sep* (default the character '.'). If not all instance names are defined for the inherited label, or if the parameter *cell_pos_name* is set, the name will be based on the name of the cell that the original label or terminal comes from, the original label or terminal name and the position of the inherited label.

  The name of an inherited label is used to name the net that is connected to it only if this net has not a normal label connected to it. For the rest, inherited labels are used in the same way as normal labels.

2.10.3 Nodes

A node represents a vertex in the circuit graph. If no resistances are extracted, exactly one node will be created for a net. If resistances are extracted (see Section 2.6), more than one node may be created for a net.

2.10.4 Node names

Default, nodes in the circuit are assigned a name that is an integer number. However, the latter is overruled in the following ways:

- A node in the circuit that represents a terminal of the cell receives a name that is equal to the terminal name.
- A node in the circuit that represents a (inherited) label of the cell receives a name that is equal to the label name.
- If resistances are extracted, if the node belongs to a net that has a name (see Section 2.10.2) and if the node does not represent a terminal nor a label, then the node has a name <netname><separator><number>, where <netname> is the net name, <separator> is specified using the parameter *net_node_sep* (default it is the character '_') and <number> is an integer number.
- If the parameter *node_pos_name* is set, each node has a name <prefix><mask>_<xpos>_<ypos>, where <prefix> is a prefix that is specified using the parameter *pos_name_prefix* (default it is an empty string), and the tuple <mask>, <xpos> and <ypos> denotes a part of the layout (mask, x coordinate and y coordinate) that corresponds to the node. It is the point that has the smallest x value and, next, the smallest y value.

Note that it is possible that a node in the output netlist has more than one name, also because during resistance extraction different nodes may be joined. Depending on the netlist format that is used, not all names may be part of the output netlist.

2.10.5 Positions of devices and sub-cells

When the option **-t** is used with *space* or when the parameter *component_coordinates* is set, positions of devices and sub-cells are added to the extracted circuit.

2.10.6 Name length

The maximum number of characters in an instance, node or net name is determined by the project version number. The project version number is given on the first line of the .dmrc file and for e.g. version number 3 the maximum name length is 14, for version number 301 the maximum name length is 32 and for version number 302 the maximum name length is 255. The *mkpr* program creates only projects for version number 302.

Node or net names that are generated by *space* and that are longer than the maximum name length allowed by the project version number, are converted to a shorter name. A translation table *cell*.nmp will then give the mapping between the original names and the new names. The maximum name length can be decreased (e.g. because the simulator that is used after the extraction can not handle the long names) by specifying a new maximum length using the parameter *max_name_length*

When a long name is converted to a short name, the parameter *trunc_name_prefix* specifies a prefix string for the new name (default is "n").

2.10.7 More back-annotation information

The use of the option **-x** or setting the parameter *backannotation* causes that *space* will also generate layout back-annotation information about the geometry of the different nets, the different transistors etc. This information can e.g. be used as input for the program *highlay*. The option **-x** or the parameter *backannotation* implies the option **-t**.

2.10.8 Parameter File

Back annotation is controlled by the following parameters from the parameter file:

parameter	type	default
hier_name_sep	char	.
inst_term_sep	char	.
no_labels	boolean	off
hier_labels	boolean	off
hier_terminals	boolean	off
leaf_terminals	boolean	off
cell_pos_name	boolean	off
term_is_netname	boolean	off
net_node_sep	char	_
node_pos_name	boolean	off
pos_name_prefix	string	<empty>
max_name_length	int	32
trunc_name_prefix	string	n
component_coordinates	boolean	off
backannotation	boolean	off

2.10.9 Command-Line Options

The following command-line options control back-annotation:

-t Add positions of devices and sub-cells to the extracted circuit.

-x Generate layout back-annotation information, implies **-t**.

2.11 Element Definition Files

Space is technology independent. At start up, it reads a tabular element definition file specifying how the different elements like conductors and transistors can be recognized from the different mask combinations, and which values should be used for for example conductor capacitivity and conductor resistivity. This tabular element file is constructed from a user-defined element definition file by the space technology compiler *tecc*.

The default element definition file is *space.def.t* in the appropriate directory of the ICD process library. However, there can be several other element definition files for a particular process. For example, the file *space.max.t* may contain an element description with worst-case capacitance and resistance values. If this file exists, it can be read rather

than the standard file by specifying **-e** *max* at the command line.

The user can also prepare his own element definition file and specify the name of that file with the **-E** option. For a description of how to prepare an element definition file, see Chapter 3. But usually it is most convenient to modify a copy of the source of one of the "official" element definition tables. These sources are also in the ICD process library.

2.11.1 Command-Line Options

The command line options are as follows:

-e *xxx*	Use the file space.*xxx*.t in the ICD process library as the element definition file.
-E *file*	Use *file* as the element definition file.

2.12 Parameter Files

The parameter file for *space* contains values for several variables that control the extraction process. For example, it contains all parameters that control the network reduction heuristics.

The default parameter file is *space.def.p* in the appropriate directory of the ICD process library. However, an alternative parameter file in the ICD process library can be used by using the **-p** option at the command line, and other files can be used by specifying the **-P** option at the command line.

Parameters can be of different types, e.g. real, integer, string and boolean. If a parameter is of type boolean, its value can be either on or off. If the name of a boolean parameter is included in the parameter file, but no value is specified, this is equivalent to specifying the value on.

Some parameters have a name *class.parameter* (e.g. sne.frequency). In this case, a group of parameters of the same class may be used without the prefix "*class.*" if they are included between the lines "BEGIN *class*" and "END *class*". E.g.

```
BEGIN sne
frequency  1e9
END sne
```

is equivalent to

```
sne.frequency  1e9
```

The value of a parameter in the parameter file can also be specified using the option **-S** *param*=*value*. This sets parameter *param* to the value *value* and overrides the setting in the parameter file. (-S *param* is equivalent to -S *param*=on.)

Some parameters can also be specified as options, e.g. the use of the option **-F** is equivalent to specifying the parameter *flat_extraction* in the parameter file. Options

overrule specifications in the parameter file and specifications using the option **-S** *param*=*value*.

2.12.1 Command-Line Options

The command line options are as follows:

-p *xxx* Use the file space.*xxx*.p in the ICD process library as the parameter file.

-P *file* Use *file* as the parameter file.

-S *param*=*value* Set parameter *param* to the value *value*, overrides the setting in the parameter (.p) file. (-S *param* is equivalent to -S *param*=on.)

3. Developing Space Element Definition Files

3.1 Introduction

The element definition file describes how *space* recognizes the circuit elements (transistors, contacts, interconnection layers etc.) from the layout definition of the cell. The element definition file further contains the values for the different interconnect capacitances, the sheet resistances for the interconnect layers, etc.

The program *tecc* acts as a pre-processor for technology descriptions for the *space* layout to circuit extractor. From a user-defined element-definition source file, *tecc* produces a compiled element-definition file that can be used as input for *space.*

3.2 Invocation and Command Line Options

The program *tecc* is invoked as follows:

`tecc` *[-sn] [-m maskdatafile] [-p process] file*

The user-defined input file should have the extension '.s', while the compiled output file will have the same name but with '.t' substituted for '.s'. The compiled output file is an ascii file, hence it can easily be exchanged between different types of machines.

3.2.1 Command-Line Options

The following options can be specified:

-s Silent mode. This will suppress some diagnostics information, see section 3.5.

-n Do not compress table-format element-definition file. This option is useful during element-definition file development. It makes *tecc* run faster, and *space* somewhat slower.

-m *maskdatafile*

Specifies the maskdatafile. Default, the maskdatafile is obtained from the process directory.

-p *process*

Specifies the process. The default process is determined by the current project directory. This option allows to run *tecc* outside a project directory.

3.3 Example Technology

In this section, we will use a double metal Nwell CMOS process as an example. This technology is known in the system under the name 'scmos_n', and the technology files can be inspected. The masks that are used are the following:

maskname	description/purpose
cpg	polysilicon interconnect
caa	active area
cmf	metal interconnect
cms	metal2 interconnect
cca	contact metal to diffusion
ccp	contact metal to poly
cva	contact metal to metal2
cwn	n-well
csn	n-channel implant
cog	contact to bondpads

The process is similar to the Mosis n-well scmos process. An element definition file for this process is included as appendix D, and a parameter file as appendix E.

For illustrating the features that are only meaningful to bipolar processes, we will use the bipolar DIMES-01 process as example. An element definition file for this process is included as appendix F. The standard masks of this process are:

maskname	description/purpose
bn	buried N-layer
dp	deep P-well; island isolation
dn	deep N-well; collectorplug of all NPNs
wp	extrinsic base of the NPNs
bw	intrinsic base of the BW-NPN
wn	shallow N-layer; washed emitter implantation
co	contact windows in wp, sn and sp
ic	interconnect layer
ct	second contact window for in-ic contact
in	second interconnect layer

3.4 The Element Definition File

3.4.1 General

The element-definition file defines the circuit elements that can be recognized from the layout description. For each of the elements, at least a *name* and a *condition list* have to be specified. In this subsection, names and condition lists are defined. They are illustrated in the next subsections.

The name of an element is used to identify the element when error messages are generated or, for transistor elements, to identify the element in the circuit that is extracted. It is not allowed to use the same name in more than one element definition.

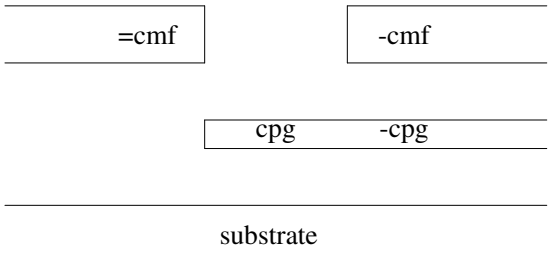
A condition list specifies how the presence of a particular element depends on the presence or absence of the different masks. The condition list is a boolean expression where the masks are used as the variables of the expression. In the expression, the AND operation is performed using simple concatenation, the OR operation is performed using the 'l' character (AND has precedence over OR) and the INVERT operation is performed using the '!' character. Parentheses may be used to nest the expression.

Example:
Examples of condition lists are:

```
caa !cpg !csn

cca cmf caa !cpg ( cwn !csn | !cwn csn )
```

References to masks in adjacent areas can be made by preceding the mask names with a '-' character (specifying an edge mask), or a '=' character (specifying an opposite edge mask). The following (cross-section) gives an example.



When preceding the mask name with a '-' character, a reference is made to a mask that is in an adjacent area. When preceding the mask name with a '=' character, a reference is made to a mask that is in an area that is opposite to the area that contains the masks preceded with the '-' sign. The above can be used to define the elements that are present on the boundary between two regions of different mask combinations (e.g. edge capacitances) or elements that are present between the boundaries themselves (e.g. lateral capacitances between parallel wires).

In the following, the syntax and semantics of the element-definition file is described. The element-definition file may contain specifications for, among other things, the units, the key list, the new masks, the mask colors, the conductor elements, the transistor elements, the connect and contact elements and the capacitance elements.

NOTE:
Each of the specifications in Sections 3.4.3-3.4.13 is optional but their order is fixed.

3.4.2 Comment
Comments can be included in the element-definition file by preceding them with a '#' character. All text following the '#' character, until the end of the line, will be skipped as comment.

Example:

```
# this is comment
```

Comment can be included at any place in the element definition file.

3.4.3 Unit specification
Syntax:

`unit` *variable value*
.
.

With an unit command, the unit of variable values used in one of the element lists can be specified. The string *variable* can be represented by the following key word:

resistance	to specify the unit for sheet resistance (see conductors),
c_resistance	to specify the unit for contact resistance (see contacts),
a_capacitance	to specify the unit for area capacitance,
e_capacitance	to specify the unit for edge capacitance or - if the capacitance is specified by means of (distance, capacitivity) pairs - also for lateral capacitance,
capacitance	to specify the unit for other (lateral) capacitance,
distance	to specify the unit for distance in (distance, capacitivity) pairs,
resize	to specify the unit for resizing masks.

For other key words see the "Space 3D Capacitance Extraction User's Manual".
The unit of each variable is specified by *value*, expressed in S.I. units.

Example:
The following gives some examples of unit specifications (between comment the new unit is described).

```
unit resistance    1     # ohm
unit c_resistance  1e-12 # ohm um^2
unit a_capacitance 1e-6  # aF/um^2
unit e_capacitance 1e-12 # aF/um
unit capacitance   1e-15 # fF
unit distance      1e-6  # um
unit resize        1e-6  # um
```

3.4.4 The key list

> **NOTE:**
> You may skip this subsection until or unless you run into problems with the size of the compiled technology file, due to a large number of masks and/or element definitions.

Syntax:

`keys:` *mask1 mask2 ... maskN*

During extraction, *space* uses a hash table to speed-up the recognition of the elements. This hash table is constructed based on the masks that are specified in the key list. When a mask is specified in the key list, *space* is capable of recognizing elements without separately checking the element conditions that refer to the presence or absence of that mask. Adjacent masks (that are specified by preceding them with a '-' character) may also be used as a key mask. Note that the size of the hash table will be proportional to 2 ^ N, where N is the number of key masks. By carefully choosing the key masks, the speed of element recognition will be optimal, while the hash table will be not too large. Actually, *space* will use two key lists, one for surface elements and one for edge elements.

When no key list is specified, but

`maxkeys` *maxkeys [maxkeys2 [maxedgekeys]]*

is specified instead, *tecc* will select the key masks itself. Up to a maximum of *maxkeys* surface mask keys for the surface element key list will be used. The most frequently used masks, specifying element conditions, will be selected. Optional, up to a maximum of *maxkeys2* surface mask keys for the edge element key list will be used. And optional, up to a maximum of *maxedgekeys* edge mask keys are also used for the edge element key list.

> **NOTE:**
> A specification of many key masks or a very large value for *maxkeys* may cause *tecc* to run out of memory, or it may result in an excessive long running time for the program.

When neither a key list nor a maximum number of keys is specified, *tecc* will assume that *maxkeys* and *maxkeys2* are equal to 12 and *maxedgekeys* is equal to 0.

Example:
When specifying for the complete element description as found in the CMOS technology library

```
maxkeys 13
```

tecc will find a key list that is equivalent to

```
-- keys: cms cpg cmf caa cwn csn cca ccp cva
-- keys2: cms cpg cmf caa cwn csn
-- number of keys: 6 + 3 (9)
-- number of keys2: 6 + 0 (6)
```

To get also six edge masks into the edge key list (keys2), specify:

```
maxkeys 13 6 6
```

But, normally no edge mask keys are used for the key list, because there are normally too many surface masks. Besides that, *space* is using an improved hash table and runs also fast with small key lists.

3.4.5 New mask specification

Syntax:

`new`: *condition_list : name*
.
.

This command allows to create a new mask from the combination of other masks. The new mask, given by *name*, is defined everywhere where the combination of masks satisfies the condition list of the specification. The characters '-' and '=' may not be used in the condition list for a new mask.

Example:

```
new : caa !cpg !csn : pdf   # mask pdf defines p+ active area
new : caa !cpg  csn : ndf   # mask ndf defines n+ active area

new : caa ( cwn !csn | !cwn csn ) : cta   # contact area

new : !dp : epi    # mask epi defines an epitaxial layer
```

3.4.6 Resize mask specification

Syntax:

`resize`: *condition_list : mask : value*
.
.

This command allows to grow masks with a certain value (when a positive value is specified) or shrink masks with a certain value (when a negative value is specified). The *mask* that is specified must be in the *condition_list* that is specified, or it must be a newly created mask name. In the last case, the new mask becomes a real mask. For one mask,

more than one resize statement may be specified.

Example:
The following grows the cpg mask with 0.01 micron.

```
resize : cpg : cpg : 0.01e-6
```

Apart from using the resize statement to model the difference between "mask dimensions" and "on-chip dimensions", it may also be used to e.g. merge arrays of small contacts into bigger contacts. This may be desirable, sometimes, in order to improve the efficiency of resistance extraction.

Example:
The following two statements will merge all 'cva' contacts that are within 0.5 micron of each other. This is achieved by first growing the 'cva' layout object with 0.25 micron, and next shrinking the newly obtained objects with 0.25 micron.

```
resize : cva : cva : 0.25e-6
resize : cva : cva : -0.25e-6
```

3.4.7 Mask colors

The colors that are used to display the different masks/conductors when using *Xspace* or *view3d,* may be specified as follows:

Syntax:

`colors` :
mask color
.
.

For a more detailed description, see the "Xspace User's Manual".

3.4.8 The conductor list

Syntax:

`conductors` [*type*] :
name : condition_list : mask : sheet-resistivity [: *carrier_type*]
.
.

The conductor list contains the definitions for the conducting layers in the circuit. For each conductor specification, a specification of the actual conductor mask and a specification of the sheet-resistivity (in ohms) is required. For bipolar devices in particular, it is also necessary to specify the *carrier-type* of the conductor. The type can be *n* for n doped conductors, *p* for p doped conductors and *m* otherwise. The default carrier-type is *m*.

Conducting layers in adjacent areas are connected to each other *if and only if* they have the same conductor mask and the same carrier type. If either the conductor mask is different or the carrier type is different, the conducting layers are not connected to each other.

Optionally, a type may be specified for the conductor list.

Example:
The following conductor section is appropriate for the CMOS example technology:

```
conductors :
    cond_mf : cmf           : cmf  : 0.045 : m  # first metal
    cond_ms : cms           : cms  : 0.030 : m  # second metal
    cond_pg : cpg           : cpg  : 40    : m  # poly interconnect
    cond_pa : caa !cpg !csn : caa  : 70    : p  # p+ active area
    cond_na : caa !cpg  csn : caa  : 50    : n  # n+ active area
```

The following describes some conductors for the bipolar example technology:

```
    condIC  : ic          : ic  : 0.044 : m
    condBW1 : bw !wn      : bw  : 600   : p
    condBW2 : bw wn       : bw  : 7000  : p
    condWN  : wn          : wn  : 40    : n   # shallow N-layer
```

Default, when extracting resistances, linear resistances will be extracted for a conductor. However, when a conductor type is specified with the conductor list, the extracted resistances for all conductors in that list will be of the specified type.

Example:

```
conductors rdif :
    cond_pa : caa !cpg !csn : caa  : 70 : p    # p+ active area
    cond_na : caa !cpg  csn : caa  : 50 : n    # n+ active area
```

In this case, a resistor model corresponding to the specified conductor type must be specified using the control file of *xspice* (see Section 4.2).

An element definition file may contain more than one conductor list.

3.4.9 The field-effect transistor list
Syntax:

`fets :`
name : condition_list : mask_g mask_ds [(*condition_list*)] [: *connect_b*]
.
.

For a field-effect transistor (e.g. MOS transistor), the name and the condition list are followed by a specification of the gate mask *mask_g* and the drain/source mask *mask_ds*. The gate mask and the drain/source mask must be masks that are defined as a conductor in the conductor list. Optionally, in parentheses, a condition list for the drain/source region can be specified. When capacitance extraction is enabled, this information will be

used to compute the parameters ad, as, pd, ps, nrs and nrd (see SPICE User's Manual) for the transistor. Further, optionally, at the end of the specification after a colon, a bulk connection *connect_b* can be specified for the transistor. This connection may consist of (1) a mask that is specified as a conductor in the conductor list, (2) the string "@sub" to denote the substrate area below the transistor gate, or (3) the notation "%(*condition_list*)" to denote a substrate area described by the condition list. When case (3) is used, the area specified by the condition list must have an overlap with the transistor gate area.

Example:
The MOS transistors can be defined as follows:

```
fets :
    nenh : cpg caa  csn : cpg caa     # nenh MOS
    penh : cpg caa !csn : cpg caa     # penh MOS
```

Note that in this example, the n-well mask 'cwn' has not been used, since it is assumed that this mask is, respectively, present or absent because the layout is free of design-rules errors (see also appendix C).

In case when the extraction of the parameters ad, as, pd, ps, nrs and nrd is required (to describe the properties of the transistor drain/source region), the following specification can be used:

```
fets :
    nenh : cpg caa  csn : cpg caa (caa !cpg  csn)   # nenh MOS
    penh : cpg caa !csn : cpg caa (caa !cpg !csn)   # penh MOS
```

When no bulk terminals are specified (as in the above transistor definition example), the program *xspice* will add appropriate bulk terminal connections when a SPICE circuit description is retrieved from the database. The actual bulk connections for field-effect transistors may be extracted by specifying also a bulk connection for each transistor.

Example:
When 'cwn' is defined as a conductor mask, the actual bulk connections may be extracted by using the following transistor definition:

```
fets :
    nenh : cpg caa  csn : cpg caa : @sub   # nenh MOS
    penh : cpg caa !csn : cpg caa : cwn    # penh MOS
```

In case of substrate resistance extraction, the above specification will result in the creation of substrate contact directly under the 'nenh' transistor gate area. When the user wants to create a substrate terminal for the 'nenh' transistor under the gate area as well as under the drain and source areas of the transistor, the following specification may be used:

```
fets :
    nenh : cpg caa  csn : cpg caa : %(caa csn !cwn)
```

The condition '!cwn' has been used here to prevent that substrate contacts are also

generated for well contacts.

3.4.10 The bipolar transistor list

Syntax:

```
bjts:
  name : condition_list : type : mask_em mask_ba mask_co [ : connect_b ]
    .
    .
```

For a bipolar junction transistor the name, the condition list and the transistor-type ("ver" for vertical or "lat" for lateral) are followed by a specification of the emitter mask *mask_em*, the base mask *mask_ba*, the collector mask *mask_co*. These masks must be defined as a conductor in the conductor list. Optionally, after a colon, a bulk connection *connect_b* may be specified for the transistor. This connection may consist of (1) a mask that is specified as a conductor in the conductor list, or (2) the notation "*%*(*condition_list*)" to denote a substrate area described by the condition list. When case (2) is used, the area specified by the condition list must have an overlap with the transistor area.

Example:
The bipolar transistors can be defined as follows:

```
bjts :
    npnBW :      wn  bw epi : ver :  wn  bw epi : %(bw wn)
    pnpWP : !wp -wp !bw epi : lat : -wp epi =wp
```

3.4.11 The connect list

Syntax:

```
connects:
  name : condition_list : mask1 mask2
    .
    .
```

The connect elements connect different semiconductor regions of the same carrier-type. They define the connectivity relation between the different conductors. *Mask1* and *mask2* are the conductor masks that are connected. Connect elements can not be used to connect conducting layers that have a different carrier-type. Note: the connection of conductor layers via a contact or via should be specified in the contact list (see section 3.4.12).

Example:

```
connects :
    connBW : bw wp      : bw wp    # connect bw and wp
    connBN : bn epi     : bn epi   # connect epi and buried layer
    connSN : sn epi !dn : sn epi   # connect epi and sn
```

3.4.12 The contact list

Syntax:

`contacts` [*type*] :
name : condition_list : mask1 mask2 : resistivity
.
.

The contact elements connect different conductors that are on top of each other. *Mask1* and *mask2* are the conductor masks that are connected by the contact. For *mask1* or *mask2* also the string "@sub" or the "*%*(*condition_list*)" notation may be used. The first specifies a connection to the substrate area directly below the contact area. The second specifies a connection to a substrate area as specified by the condition list. In the second case, the substrate area described by the condition list must have an overlap with the contact area. The resistivity parameter specifies the contact resistance in ohm square meter for a (hypothetical) contact of 1 meter * 1 meter. Optionally, a type may be specified for the contact list.

Example:

```
contacts :
    cont_s : cva cmf cms      : cmf cms : 1e-12   # metal to metal2
    cont_p : ccp cmf cpg      : cmf cpg : 100e-12 # metal to poly
    cont_a : cca cmf caa !cpg : cmf caa : 100e-12 # metal to active
    cont_b : cca cmf !cwn !csn: cmf @sub: 100e-12 # metal to sub.
```

Default, when extracting resistances, linear resistances will be extracted for a contact. However, when a contact type is specified with the contact list, the contact resistances for all contacts in that list will be of the specified type. An element definition file may contain more than one contact list.

3.4.13 The capacitance list

Syntax:

[`junction`] `capacitances` [*type*] :
name : condition_list : mask1 [mask2] : capacitivity
.
.

In the capacitance list, coupling capacitances, ground capacitances and substrate capacitances can be defined.

Coupling capacitances are defined by using a conductor mask for both *mask1* and *mask2*.

Ground capacitances are defined by using the string "@gnd" for either *mask1* or *mask2*, or by omitting *mask2*. In this case, the capacitance will on one side be connected to a node that is called "GND".

Substrate capacitances are defined by using the string "@sub" or the notation "%(*condition_list*)" for either *mask1* or *mask2*. In this case, the capacitance will on one side be connected - when no substrate resistances are extracted - to a node that is called "SUBSTR", or - when substrate resistances are extracted, see the "Space Substrate Resistance Extraction User's Manual" - to a node that corresponds to a substrate terminal. In case of substrate resistance extraction, the use of the string "@sub" will denote the substrate area directly under the capacitance area, while the notation "%(*condition_list*)" is used to denote a substrate area specified by the condition list, which must enclose the capacitance area.

Capacitances are further distinguished between surface capacitances, edge capacitances and lateral capacitances.

To define edge capacitance, masks preceded with a '-' character are used in the condition list, and either *mask1* or *mask2*, or both, have to be preceded with a '-' character to denote an edge of an interconnection.

To define lateral capacitances, masks preceded with a '-' character and mask preceded with a '=' character are used in the condition list, and either *mask1* or *mask2* is preceded with a '-' character to denote one edge of an interconnection and the other mask is preceded with a '=' character to denote another (opposite) edge of an interconnection.

For surface capacitances, *capacitivity* is the capacitance per square meter. For edge capacitances and lateral capacitances, the capacitance can be specified in two different ways.

For edge capacitances, if only one value is specified (as in the above), *capacitivity* is the capacitance per meter edge length.

For lateral capacitances, if only one value is specified (as in the above), *capacitivity* is the capacitance for a configuration where the spacing between two parallel wires is equal to length of the two wires. In that case, it is assumed that the lateral coupling capacitance is proportional to the distance between the two wires and inverse proportional to their spacing, see Section 2.5.3.

Edge capacitances and lateral capacitances can also be defined as follows.

name : condition_list : mask1 mask2 : distance1 capacitivity1
distance2 capacitivity2
.
.

In this case, for edge capacitances, the distance, capacitivity pairs specify the capacitance per meter edge length for a given distance to a neighboring wire that is of the same type. In that case, a lateral coupling capacitance must also be defined for these wires. If no lateral coupling capacitance is defined or if the distance between the wire and the neighboring wire is larger than the maximum distance for which an edge capacitance is

specified, the edge capacitance is equal to the edge capacitance that is specified with the maximum distance.

For the lateral capacitances, the distance, capacitivity pairs specify the capacitance between two parallel wires of a length of 1 meter for different values of the distance between them.

For both edge capacitances and lateral capacitances, capacitances for other configurations are found from an interpolation between two distance, capacitivity pairs (see Section 2.5.3 and Section 2.5.4).

Example:
The following three lines specify first metal bottom to ground capacitance, first metal sidewall to ground capacitance and the lateral coupling capacitance between two parallel first metal lines under the condition that no second metal is present:

```
capacitances:
    acap_cmf_sub :  cmf                !cpg !caa : cmf @gnd: 25e-06
    ecap_cmf_sub : !cmf -cmf      !cms !cpg !caa :-cmf @gnd: 52e-12
    lcap_cmf     : !cmf -cmf =cmf !cms !cpg !caa :-cmf =cmf: 30e-18
```

The following line specifies the coupling capacitance between the edge of a first metal wire and the edge of a second metal wire that are on top of each other:

```
capacitances:
    eecap_cmf_cms : !cmf -cmf !cms -cms : -cmf -cms : 23e-12
```

The first three capacitances may (more accurately) be specified as a function of the distance between two neighboring wires as follows:

```
capacitances:
    acap_cmf_sub :  cmf                !cpg !caa : cmf @gnd: 25e-06
    ecap_cmf_sub : !cmf -cmf      !cms !cpg !caa :-cmf @gnd:
                                                        1e-6 30e-12
                                                        2e-6 46e-12
                                                        4e-6 50e-12
                                                        8e-6 52e-12

    lcap_cmf     : !cmf -cmf =cmf !cms !cpg !caa :-cmf =cmf:
                                                        1e-6 27e-12
                                                        2e-6  8e-12
                                                        4e-6  3e-12
                                                        8e-6  1e-12
```

There may be more than one capacitance list in an element definition file. Optionally, for each capacitance list a type may be specified after the keyword "capacitances". In that case, all capacitance definitions in that list are of the specified type, and the extracted capacitances will also have that type.

Normally, the positive node and the negative node of the extracted capacitance will be arbitrarily connected to the layers that are specified with *mask1* and *mask2*. However, for capacitance lists for which a type is specified, if the keyword "junction" is used before the

keyword "capacitances" for all elements in that list *mask1* specifies the positive node of the element and *mask2* specifies the negative node of the element. For junction capacitances, the method of extraction is further determined by the parameter *jun_caps* (see Section 2.5.7). Lateral coupling capacitances may not be specified for junction capacitances.

Example:
Junction capacitances of type 'ndif' for n diffusion areas and junction capacitances of type 'pdif' for p diffusion areas may be specified as follows:

```
junction capacitances ndif :
    acap_na:  caa       !cpg  csn  !cwn :  caa @gnd : 100e-6
    ecap_na: !caa -caa !-cpg -csn !-cwn : -caa @gnd : 300e-12

junction capacitances pdif :
    acap_pa:  caa       !cpg  !csn cwn     : caa cwn : 500e-6
    ecap_pa: !caa -caa !-cpg !-csn cwn -cwn:-caa cwn : 600e-12
```

In order to simulate a circuit that contains junction capacitances, a corresponding (diode) model has to specified for each type ('ndif' and 'pdif' in the above example) using the control file of *xspice.*

3.5 Diagnostics

Without the **-s** option, *tecc* will print information about the hash table that is being constructed for element recognition. This information can be used to tune the specification of the key masks.

Furthermore, *tecc* will check if legal mask names are used and if conductor masks are used with transistor, contact and capacitance definitions. During extraction itself it will be checked if appropriate conductor elements are present; for transistor elements and capacitance elements this is required, for contact elements this is not required.

4. Preparing Simulation Input

4.1 Introduction

After extraction, a circuit description can be obtained using on of the programs *xedif, xnle, xpstar, xsls, xspice* or *xvhdl,* depending on the desired netlist format. Here will we discuss the retrieval of circuit description in the SPICE format using the program *xspice,* to prepare input for the SPICE simulator. However, several things that are said here are also valid for the other netlist formats. For a more precise description of the retrieval of other netlist formats, see the manual page of the corresponding program.

The model descriptions of the devices that occur in the SPICE circuit are normally specified using the control file of *xspice.* The model parameters may be specified as a function of some layout parameters like the transistor emitter area and perimeter and the transistor base width. In the control file also instance specific information can be specified like a prefix for each instance name of a device and the format for printing the instance parameters of each device.

Optionally, the program *putdevmod* can be used to specify a model for a device. This method is useful if the model for the device consists of more than just a standard transistor model e.g. if it is described by one or more subcircuits in combination with one or more transistor models.

4.2 Describing SPICE Models using the Control File of Xspice

The following table lists the layout parameters that are computed by the extractor for the different devices.

symbol	description	devices
w	transistor width	fet transistors
l	transistor length	fet transistors
ad	drain area	fet transistors
as	source area	fet transistors
pd	drain perimeter	fet transistors
ps	source perimeter	fet transistors
nrd	equivalent drain squares	fet transistors
nrs	equivalent source squares	fet transistors
ae	emitter area	bjt transistors
pe	emitter perimeter	bjt transistors
wb	base width	lateral bjt transistors
v	value	resistors and (junction) capacitors
area	junction area	junction capacitors
area<nr>	junction area	junction capacitors
perim	junction perimeter	junction capacitors
perim<nr>	junction perimeter	junction capacitors

The parameters ad, as, pd, ps, nrd and nrs are only computed for a fet transistor when a condition list is specified for its drain/source region in the element definition file and when capacitance extraction is enabled. Which of the layout parameters are computed for junction capacitors (e.g. v, area or area<nr>) depends on the value of the parameter *jun_caps* (see Section 2.5.7).

4.2.1 The control file

The default name of the control file of *xspice* is *xspicerc*. First, *xspice* tries to read this file from the current working directory. Otherwise, it tries to open it in the process directory.

In the control file, the models are included by specifying them in one or more separate files called the library files. These files are then included in the control file as follows:

`include_library` *file_name*

For how the models are described in the library file, see Section 4.2.2.

Different models can be selected for each extracted device, based on the values of the parameters of the device. This is specified by the so-called global model-specifications. The global model-specifications are of the following format:

`model` *name orig_name type_name* `[(` *range_specs* `)]`

The *orig_name* has to be equal to the extracted device name, which is equal to the name specified in the element definition file. The *type_name* has to be equal to one of the following SPICE standard device-models: *npn*, *pnp*, *nmos*, *pmos*, *r*, *c* or *d*. Optionally, *range_specs* can be specified for the device geometries for which the model is valid. For each layout parameter a range can be specified according to one of the following formats:

layout_parameter typical_val
layout_parameter lower_val upper_val
layout_parameter lower_val typical_val upper_val

The range values can be expressions in terms of other layout parameters that are specified (the expression must be between parentheses and the name of the other layout parameters must be preceded by a '$'-sign). It is allowed to specify only the typical value or to omit this value from the range specification.

Based on the values that are specified for the layout parameters of one particular global model-definition, the following situations can be distinguished:

- **Only the typical values are specified**
  The device model is only valid for one specific device. The parameters for this device model are all known. The model is selected if the layout parameters of the extracted device exactly match the typical values as specified.
- **Both typical and upper/lower values are specified**
  Extracted devices for which the layout parameters are within the specified ranges are assigned to this model and a scaling factor is included. The scaling factor is based on the typical value of the emitter area. Also for this model all model parameters are known and specified in the library file.
- **Only upper/lower values are specified**
  For the extracted devices that cannot be assigned to models as described above, a so called *substitution model* is used. If the layout parameters of a device are within the range specification of such a model, a device specific model is created. The parameters of this model are expressions in terms of the layout parameters and must be computed for each different device geometry, see Section 4.2.2. Additionally, the name of such a model is extended by a suffix that depends on the values of the layout parameters.

  Example:
  The following gives an example of a control file for *xspice.* It contains a global model-specification of a bipolar vertical npn-transistor that is extracted as a device with name npnBW. Under the conditions with respect to emitter area and emitter perimeter that are listed with the global model-specification, the device npnBW is assigned a model bw101x that is included in the library file *spice3f3.lib*.

```
include_library spice3f3.lib

model bw101x npnBW npn (
    ae 4e-12 2e-11
    pe (2*$ae / 2e-6 + 4e-6)
)
```

Also instance-specific information for each device can be specified in a control file. The format of a specification of a prefix for each instance name of a device is as follows:

`prefix` *name prefix*

The *name* can be the *orig_name* or the *type_name* of the device. A new prefix overrides a previous specified prefix. For SPICE, the first letter of the prefix must be a legal standard device-model letter (e.g. 'm' for MOS transistors). For SPICE normally only one prefix letter is used. To use more prefix letters (max. 7) specify the following keyword:

`long_prefix`

For a device of type *type_name*, a bulk voltage *value* may be specified in the control file according to the following format.

`bulk` *type_name value*

If a bulk voltage is specified, *xspice* will automatically add a bulk terminal for the device and it will connect it to the specified potential. Up to a maximum number of 2 different values for bulk voltages may be specified in the control file.

For a device, instance parameters may be specified as follows:

`params` *name* [*model_name*] { *param_spec1 param_spec2 ...* }

The *name* can be the *orig_name* or the *type_name* and can optionally be followed by the *model_name*. A new params-statement overrides a previous specified params-statement. With the params-statement the printing order of parameter values (with or without parameter name) can be changed. Normally invisible parameters can be made visible or used. Standard visible parameters can be left out or changed. The parameter specifications *param_spec1*, *param_spec2* etc. each must have one of the following forms:

parameter=value
value
parameter=$intern_par[<operator><value>]
$intern_par[<operator><value>]

with *$intern_par* denoting the actual value of a parameter that is internally (in the database) called 'intern_par' (see the table at the beginning of Section 4.2 for a list of possible parameter names). If the *$intern_par* does not exist in the instance attribute-list, the parameter specification is left out! If the *$intern_par* is a standard visible parameter, it is no more printed in the standard way. If the "*$intern_par*"-forms have a leading '!'

sign, they are not printed. This is the way to skip a standard visible parameter. If the "*$intern_par*"-forms have two leading '!' signs, they are printed in the comment-part. The "*$intern_par*"-forms can optionally be followed by an <operator> and a <value>. This <value> may also be another internal parameter. The operation is only done, if this internal parameter exists and is not zero. This <operator> can be a '+', '-', '*' and '/'. At last, you can additionally use the '@' <operator> with a <string>. Denoting that the <string> must be printed after the value.

Other program build-in internal parameters are:

mname	the used model name
msf	the scale factor for scalable models (default 1)

Example:
The following specifies that for instances of the capacitance model 'ndif', the area of the element is represented by the parameter 'area' and the perimeter of the element is represented by the parameter 'pj'.

```
params ndif { area=$area pj=$perim }
```

The following uses square micron and micron as units for respectively the area and the perimeter.

```
params ndif { area=$area*1e12 pj=$perim*1e6 }
```

For a complete overview of all possible statements in the control file, see the manual page of *xspice.*

4.2.2 The library file

The library file contains the actual model definitions, possibly as a function of the layout parameters. Besides a specification of the model parameters, it is also allowed to define so called unity parameters in a library file. These parameters can be used in the expressions for the model parameters and are formatted as follows:

`unity` *name value*

The detailed model specifications are of the following format:

`model` *name type_name* `(` *par_list* `)`

The *type_name* is normally a standard SPICE model name, but can also be an alternative simulator model name. For each parameter in the list *par_list* the name is specified and its expression or value. (But, also only a parameter name may be specified, or a parameter name and an equal sign and another name in place of the expression.) Each expression is an equation in terms of operators and operands. Operands can be values or unity/layout parameters. In the latter case, the operand must be preceded by a '$'-sign. A value can be followed by an unit sign (a, f, p, n, u, m, k, M, G, T, P) in place of e-notation. The operators that can be used are listed below:

symbol	operator
+	addition
-	subtraction
*	multiplication
/	division
^	power

Example:
An example model specification of the model described above is as follows:

```
unity ISs_wn_bw 5.6e-7
unity ISe_wn_bw 4.9e-13

model bw101x npn (Is=$ISs_wn_bw*$ae+$ISe_wn_bw*$pe Bf=117
          Vaf=55 Br=4 Xtf=(4.7e-2*$ae+1.9e-2*$pe)^2
          Xtb=1.5 Var=4 Tf=20p)
```

4.3 The Use of the Program Putdevmod

With the program *putdevmod* device model descriptions are stored into the database as a circuit cell. This method is required if the model for the device consists of more than just a standard transistor model e.g. if it is described by one or more subcircuits in combination with one or more transistor models. Note that in order to use *putdevmod* to store model descriptions for a cell, the extraction status of the cell must be set to "device" using the program *xcontrol.*

4.3.1 Syntax and semantics of the input file

On the first line of an input file for the program *putdevmod* there is the keyword "device" followed by the name of the device. On a next line the keywords "begin spicemod" are specified to denote the beginning of the SPICE device information. The next lines are considered to be SPICE input that can directly be appended to a SPICE network description. When a SPICE circuit description is retrieved using *xspice,* the SPICE model description of a device that has been added to the database using *putdevmod,* will automatically be added at the end of the network description if the device is part of the network and if a model description of the device does not occur in a library file (see the previous section). The end of the SPICE input is denoted by a line that contains the keyword "end".

In the part of the input file that is used as SPICE input, the terminals, a possible bulk potential and a prefix for instance names for the device, may be included as SPICE comment. This is done by specifying them on lines that start with the comment character '*'.

To specify the terminals, use the keyword "terminals" followed - on the same line and separated by spaces and/or tabs - by the names of the terminals. The order in which the

terminals are specified in this file must agree with the order in which the terminals are required in the SPICE circuit description (see the Spice User's Manual). *Space* uses the following terminal names for the devices: "g", "d" and "s" for the gate, drain and source of field-effect transistors, "c", "b" and "e" for the collector, base and emitter of bipolar transistors, and "n" and "p" for the terminals of resistors and capacitors.

A bulk voltage (if appropriate) may be specified by the keyword "bulk" followed by a floating point number.

A prefix character for the instance names of the device is specified by the keyword "prefix", followed by a character.

An example of an input file for *putdevmod* is given below:

```
device lnpn
begin spicemod
* terminals  c b e
* bulk       0
* prefix     q
.model lnpn npn
+    is=6.4e-16     bf=160       vaf=100   ikf=3e-2
+    ise=2.859e-15  ne=1.476     br=3      var=20
+    ikr=0.04       isc=1e-14    nc=1.15   rb=80
+    irb=2.0e-5     rbm=15       rc=150    re=2
+    cje=0.68e-12   mje=0.34     vje=0.71  fc=0.63
+    cjc=6.8e-13    mjc=0.33     vjc=0.55  xcjc=0.19
+    tf=4.2e-10     tr=7.0e-8    xtb=1.6   xti=3
+    eg=1.16        cjs=3.1e-12  mjs=0.35  vjs=0.5
end
```

Appendix A: Summary of Command-Line Options

The program *space* (or *space3d*) has the following options:

-c	Extract capacitances to substrate.
-C	Extract coupling capacitances as well as capacitances to substrate. This option implies **-c**.
-l	Also extract lateral coupling capacitances, implies **-C**.
-3	Use a boundary-element technique for 3-dimensional capacitance extraction. Use with **-c** or **-C**.
-r	Extract resistances for high-resistivity (non-metal) interconnect.
-R	Extract all resistances, also low-resistivity metal interconnect. To use this option, it must be specified in the first option argument list. And this option argument must start with **-%**.
-z	Apply mesh refinement for resistance extraction, implies **-r**.
-G	Extract RC models that are accurate up to a certain frequency.
-b	Use a simple but fast method to compute substrate resistances.
-B	Use a boundary-element technique to compute substrate resistances.
-F	Set flat extraction mode, i.e. produce a flattened netlist.
-T	In hierarchical mode, only extract the top cell(s).
-I	Unset incremental (hierarchical) mode: do not skip sub-cells for which the circuit is up-to-date. Cannot be used with the **-F** option.
-D *depth*	Selectively unset incremental (hierarchical) mode for all cells at level <= *depth* (default *depth* = 1).
-u	Do not automatically run the preprocessors *makeboxl(1ICD)* and *makegln(1ICD).*
-n	Do not apply the circuit reduction heuristics.
-t	Add positions of devices and sub-cells to the extracted circuit.
-v	Print run-time information (verbose mode).
-h	Print help information.
-i	Print statistics, implies **-v**.

-k Selective resistance extraction, resistances are only extracted for specified interconnects.

-j Selective resistance extraction, resistances are extracted for all but specified interconnects.

-x Generate layout back-annotation information, implies **-t**.

-X Run in *Xspace* mode (see the Xspace User's Manual).

-a *sec* Make space report its progression every *sec* seconds. Space also reports its progression when it receives an ALARM signal, such a signal can be send by the command "kill -ALRM *pid*", where *pid* is the process id.

-e *xxx* Use the file space.*xxx*.t in the ICD process library as the element definition file.

-E *file* Use *file* as the element definition file.

-p *xxx* Use the file space.*xxx*.p in the ICD process library as the parameter file.

-P *file* Use *file* as the parameter file.

-S *param*=*value* Set parameter *param* to the value *value*, overrides the setting in the parameter (.p) file. (-S *param* is equivalent to -S *param*=on.)

-s *scene_file* To generate a *scene_file* for the *view3d* program.

Appendix B: Hierarchy and Terminals

With hierarchical extraction, the extracted circuit is most accurate when the following guidelines are followed.

- The area occupied by a terminal should be minimal. This is to improve the accuracy of hierarchical resistance extraction. It is recommended to use the minimal width design rule to construct a terminal box (useless error reports from a design rule checker are prevented this way).
- Do not overlap terminals (in the same interconnect layer) of two instances, but instead have them abut each other. Also, when a cell contains an instance of a child-cell: do not let the interconnect of the top-cell overlap the terminals of the child-cell, but make them abut. This is to improve the accuracy of hierarchical capacitance extraction.
- When possible, do not make layout patterns at a higher hierarchical level in the area occupied by instantiated child-cells, even if this does not change the functional behavior of the child-cell. Whenever possible, global wiring above instances should be contained in these instances. This is to more accurately determine the parasitic coupling capacitance.
- If the above rules do not apply to one or more sub-cells of a particular design, selectively set the macro status for each of these cells in order to enforce a flat extraction extraction of these sub-cells, even in case of hierarchical extraction (see Section 2.2.3). This may especially be useful for sea-of-gates circuits.

Appendix C: Solving Problems

- **Design rule correctness of the circuit**
  Often, the element definition file of *space* will be created under the assumption that the layout to be extracted is free of design rule errors. For example, the rules for transistor recognition in the *scmos_n* example technology do not require the presence or absence of the n-well mask since this is already enforced—under the assumption of design-rule correctness—by the presence or absence of the n-channel implant mask. So, in the case of unexpected extraction results, make sure that the layout is free of design rule errors.

- **Size of compiled element definition file**
  The element definition file of *space* is compiled by the program *tecc* into a form that is read in by *space*. The size of this compiled file is mostly dependent on the number of masks defined for the technology. For the *scmos_n* example technology, the size of this file is approximately 7 Kbyte. In some occasions (e.g. for other technologies), the size of this file may become too large. Then, the size of the file can be limited by lowering the value of the *maxkeys* parameter in the element definition file (see Section 3.4.4). However, extraction will run somewhat slower then.

- **New version of compiled element definition file**
  The element definition file is reorganized. It contains two key lists and these key lists are encoded. Thus, the size of this compiled file is much smaller. As a consequence, *space* does not more read older file versions.

- **Negative resistances and/or capacitances**
  When negative resistances and/or capacitances occur in the extraction output, read the note about mesh generation in Section 2.6.

- **Long extraction times with resistance extraction**
  Sometimes, when resistances are extracted, arrays of small contacts will drastically increase the extraction time. In that case, merge the contact arrays into large contacts, using the resize statement (see Section 3.4.6). Further, long extraction times may occur (1) when well resistances are extracted - especially in combination with the option **-z** - (2) when metal resistances are extracted or (3) when coupling capacitances are extracted. Improvements may then be obtained by the use of the parameter *max_delayed* (see Section 2.6.6, for cause (1), (2) and (3)), the parameter *equi_line_ratio* (see Section 2.8.11, for cause (2)) and the parameter *frag_coup_cap* (see Section 2.8.9, for cause (3)).

Appendix D: Element Definition File for CMOS Example Process

```
#
# space element definition file for scmos_n example process
#
# masks:
# cpg - polysilicon interconnect        ccp - contact metal to poly
# caa - active area                     cva - contact metal to metal2
# cmf - metal interconnect              cwn - n-well
# cms - metal2 interconnect             csn - n-channel implant
# cca - contact metal to diffusion      cog - contact to bondpads
#
# See also: maskdata

unit resistance    1     # ohm
unit c_resistance  1e-12 # ohm um^2
unit a_capacitance 1e-6  # aF/um^2
unit e_capacitance 1e-12 # aF/um
unit capacitance   1e-15 # fF

maxkeys 13

colors :
    cpg   red
    caa   green
    cmf   blue
    cms   gold
    cca   black
    ccp   black
    cva   black
    cwn   glass
    csn   glass
    cog   glass
    @sub  pink

conductors :
  # name    : condition     : mask : resistivity : type
    cond_mf : cmf           : cmf  : 0.045       : m    # first metal
    cond_ms : cms           : cms  : 0.030       : m    # second metal
    cond_pg : cpg           : cpg  : 40          : m    # poly interconnect
    cond_pa : caa !cpg !csn : caa  : 70          : p    # p+ active area
    cond_na : caa !cpg  csn : caa  : 50          : n    # n+ active area

fets :
  # name : condition    : gate d/s
    nenh : cpg caa  csn : cpg  caa     # nenh MOS
    penh : cpg caa !csn : cpg  caa     # penh MOS

contacts :
  # name   : condition        : lay1 lay2 : resistivity
    cont_s : cva cmf cms      : cmf  cms  :   1    # metal to metal2
    cont_p : ccp cmf cpg      : cmf  cpg  : 100    # metal to poly
    cont_a : cca cmf caa !cpg : cmf  caa  : 100    # metal to active area
```

```
junction capacitances ndif :
  # active area capacitances
  # name    :  condition                 : mask1 mask2 : capacitivity
    acap_na :  caa       !cpg  csn !cwn  :  caa @gnd : 100  # n+ bottom
    ecap_na : !caa -caa !-cpg -csn !-cwn : -caa @gnd : 300  # n+ sidewall

junction capacitances pdif :
    acap_pa :  caa       !cpg  !csn cwn      :  caa @gnd : 500 # p+ bottom
    ecap_pa : !caa -caa !-cpg !-csn cwn -cwn : -caa @gnd : 600 # p+ sidewall

capacitances :
  # polysilicon capacitances
    acap_cpg_sub :  cpg               !caa :  cpg @gnd : 49 # bottom to sub
    ecap_cpg_sub : !cpg -cpg !cmf !cms !caa : -cpg @gnd : 52 # edge to sub

  # first metal capacitances
    acap_cmf_sub :  cmf           !cpg !caa :  cmf @gnd : 25
    ecap_cmf_sub : !cmf -cmf !cms !cpg !caa : -cmf @gnd : 52

    acap_cmf_caa :  cmf      caa !cpg !cca !cca :  cmf caa : 49
    ecap_cmf_caa : !cmf -cmf caa !cms !cpg      : -cmf caa : 59

    acap_cmf_cpg :  cmf      cpg !ccp :  cmf  cpg : 49
    ecap_cmf_cpg : !cmf -cmf cpg !cms : -cmf  cpg : 59

  # second metal capacitances
    acap_cms_sub :  cms      !cmf !cpg !caa :  cms @gnd : 16
    ecap_cms_sub : !cms -cms !cmf !cpg !caa : -cms @gnd : 51

    acap_cms_caa :  cms      caa !cmf !cpg :  cms caa : 25
    ecap_cms_caa : !cms -cms caa !cmf !cpg : -cms caa : 54

    acap_cms_cpg :  cms      cpg !cmf :  cms cpg : 25
    ecap_cms_cpg : !cms -cms cpg !cmf : -cms cpg : 54

    acap_cms_cmf :  cms      cmf !cva :  cms cmf : 49
    ecap_cms_cmf : !cms -cms cmf      : -cms cmf : 61

    lcap_cms     : !cms -cms =cms    : -cms =cms : 0.07

#EOF
```

Appendix E: Parameter File for CMOS Example Process

```
#
# space parameter file for scmos_n example process
#
min_art_degree    3
min_degree        4
min_res         100      # ohm
max_par_res      20
no_neg_res       on
min_coup_cap      0.05
lat_cap_window    6.0    # micron
max_obtuse      110.0    # degrees
equi_line_ratio   1.0
```

Appendix F: Element Definition File for Bipolar Example Process

```
#
# space element-definition file for DIMES-01
#
# masks:
# bi - intrinsic base bi-npn (optional) dp - deep p-well
# bn - buried n-layer                   ic - interconnect
# bs - intrinsic base bs-npn (optional) in - second interconnect
# bw - intrinsic base bw-npn            sn - emitter bs-npn (optional)
# ci - channel p-jfet (optional)        sp - extrinsic base bs-npn (optional)
# co - contact window                   wn - shallow n-layer
# ct - second contact window            wp - extrinsic base bw/bi-npn
# dn - deep n-well
#
# See also: Design manual DIMES-01 process

unit c_resistance  1e-12
unit a_capacitance 1e-03
unit e_capacitance 1e-09

maxkeys 10

new : !dp : epi

colors :
    bn glass
    dp green
    dn magenta
    sp red
    sn red
    bs lightBlue
    bi brown
    ci brown
    cw glass
    wp red
    bw lightBlue
    wn red
    co white
    ic blue
    ct white
    in red

conductors :

  condIC   : ic          : ic  : 0.044 : m
  condIN   : in          : in  : 0.019 : m
  condEPI  : epi !wp !sp : epi : 0     : n
  condEPI1 : epi  wp !sp : epi : 0     : n   # Epi under WP
  condEPI2 : epi !wp  sp : epi : 0     : n   # Epi under SP
  condBN   : bn          : bn  : 20    : n
  condDP   : dp          : dp  : 8     : p   # deep P-well
  condDN   : dn          : dn  : 4     : n   # deep N-well
  condSP   : sp          : sp  : 25    : p
  condSN   : sn          : sn  : 29    : n
  condBS   : bs !sn      : bs  : 1200  : p
```

```
  condBS1  : bs  sn      : bs  : 6000  : p
  condBI   : bi !wn      : bi  : 1400  : p
  condBI1  : bi  wn      : bi  : 6000  : p
  condCI   : ci !wn      : ci  : 6000  : p
  condCI1  : ci  wn      : ci  : 30    : p
  condWP   : wp          : wp  : 25    : p
  condBW   : bw !wn      : bw  : 600   : p
  condBW1  : bw  wn      : bw  : 7000  : p
  condWN   : wn          : wn  : 40    : n   # shallow N-layer

fets :

  jfet : wn ci bn : wn ci

bjts :

  npnBS : bn sn bs epi               : ver : sn bs epi
  npnBW : bn wn bw epi               : ver : wn bw epi
  npnBI : bn wn bi epi               : ver : wn bi epi
  pnpWP : bn !wp -wp !bw !bi !ci epi : lat : -wp epi =wp
  pnpSP : bn !sp -sp !bs epi         : lat : -sp epi =sp

connects :

  connBS  : sp bs          : sp bs
  connDN  : dn epi         : dn epi
  connWN  : wn dn          : wn dn
  connBI  : bi wp          : bi wp
  connCI  : ci wp          : ci wp
  connBW  : bw wp          : bw wp
  connDP  : dp wp          : dp wp
  connSN  : sn epi !bs !dn : sn epi
  connSN1 : sn dn          : sn dn
  connBN  : bn epi         : bn epi

contacts :

  contIN : ic ct in  : ic  in :   0
  contSN : ic co sn  : ic  sn : 120
  contSP : ic co sp  : ic  sp :  16
  contWN : ic !co wn : ic  wn :  80
  contWP : ic co wp  : ic  wp : 160
  contDN : ic co dn  : ic  dn :  80

capacitances :

  capBS  : ic  bs !sn             : ic  bs  : 0.109
  capEPI : ic !bn !dp             : ic  epi : 0.123
  capSP  : ic  sp !co !bs         : ic  sp  : 0.119
  capSN  : ic  sn !co             : ic  sn  : 0.077
  capBI  : ic  bi !wn             : ic  bi  : 0.110
  capCI  : ic  ci !wn             : ic  ci  : 0.051
  capWP  : ic  wp !co !bi !bw !ci : ic  wp  : 0.124
  capBW  : ic  bw !wn             : ic  bw  : 0.122
  capDP  : ic  dp !wp !bw         : ic  dp  : 0.123
  capDN  : ic  dn !wn !sn !co     : ic  dn  : 0.081

#EOF
```

Appendix G: Parameter File for Bipolar Example Process

```
#
# space parameter file for DIMES-01 process
#
min_art_degree    3
min_degree        4
min_res          10      # ohm
max_par_res      20
no_neg_res       on
min_coup_cap      0.05
lat_cap_window    6.0    # micron
lat_base_width    3.0    # micron
max_obtuse      110.0    # degrees
equi_line_ratio   1.0
```

Appendix H: Control File for Bipolar Example Process

```
# library_files specifies which file(s) contain
# the appropriate model definitions.

include_library  spice3f3.lib

# model indicates which predefined models can be
# used for which group of devices and it includes
# the ranges for area (AE), perimeter (PE) and
# (for lateral pnp) base width (WB).

model bw101a  npnBW  npn (
        AE 4e-12 8e-12 4e-11
        PE (2*$AE / 2.00e-06 + 4.00e-06)
)
model bw10x  npnBW  npn (
        AE 4e-12 2e-10
        PE 8e-06 6e-05
)
model bs101a  npnBS  npn (
        AE 3.60e-11
        PE 2.40e-05
)
model bi101a  npnBI  npn (
        AE 8.00e-12
        PE 1.20e-05
)
model wp102c  pnpWP  pnp (
        AE 3.60e-11
        PE 2.4e-05
        WB 3.00e-06
)
```

Appendix I: Library File for Bipolar Example Process

```
# In this file, the models are described for the different bipolar
# devices of the DIMES-01 process. It is allowed to create models
# for which the parameters are defined by a substitution equation.

unity Q_electron      1.602e-19
unity N_intrinsic     1.045e+20
unity Gummel_base     7.500e+06
unity C0s_wn_bw       1.900e-03
unity C0e_wn_bw       2.800e-09
unity C0s_bw_epi      0.290e-03
unity C0s_bn_sub      0.151e-03

model bw10x  npn (Is=($Q_electron*$N_intrinsic/$Gummel_base)*$AE Nf=1
             Ikf=3.00e+07*$AE+6.00e+01*$PE Bf=117 Br=4 Vaf=55 Var=4
             Ikr=5.00e+07*$AE+1.00e+02*$PE Xtb=1.5 Eg=1.17 Xti=2.5
             Cje=$C0s_wn_bw*$AE+$C0e_wn_bw*$PE Vje=0.78 Mje=0.28 Tf=20p
             Xtf=(4.70e-02*$AE+1.90e-02*$PE)^2 Tr=100p Mjc=0.32 Vjc=0.67
             Cjc=$C0s_bw_epi*$AE Cjs=$C0s_bn_sub*$AE Vjs=0.45 Mjs=0.26)

model bw101a npn (Is=0.018f Bf=117 Nf=1 Vaf=55 Ikf=4.1m Br=4 Nr=1 Var=4
             Ikr=45u Rb=600 Irb=0.15m Rbm=30 Re=14 Rc=200 Xtb=1.5
             Eg=1.17 Xti=2.5 Cje=50f Vje=0.78 Mje=0.28 Tf=20p Cjc=75f
             Vjc=0.67 Mjc=0.32 Xcjc=1 Tr=100p Cjs=0.24p Vjs=0.45 Mjs=0.26)

model bs101a npn (Is=0.050f Bf=100 Nf=1 Vaf=40 Ikf=5m Ise=1f Ne=2 Br=0.5
             Nr=1 Var=5 Ikr=5m Isc=10f Nc=1.2 Rb=350 Irb=1m Rbm=50 Re=25
             Rc=150 Eg=1.17 Xti=3 Cje=95f Vje=0.8 Mje=0.26 Tf=30p Cjc=100f
             Vjc=0.75 Mjc=0.33 Xcjc=1 Tr=100p Cjs=0.25p Vjs=0.45 Mjs=0.26)

model bi101a npn (Is=0.018f Bf=120 Nf=1 Vaf=58 Ikf=4.2m Br=4 Nr=1 Var=5.8
             Ikr=45u Rb=600 Irb=0.15m Rbm=30 Re=14 Rc=200 Xtb=1.5 Eg=1.20
             Xti=2.5 Cje=40f Vje=0.77 Mje=0.24 Tf=30p Cjc=75f Vjc=0.65
             Mjc=0.32 Xcjc=1 Tr=100p Cjs=0.24p Vjs=0.45 Mjs=0.26)

model wp102c pnp (Is=0.183f Bf=89 Nf=1 Vaf=13 Ikf=0.5m Ise=0.37f Ne=2 BR=17
             Nr=1 Var=10 Ikr=0.4m Isc=1.4f Nc=2 Rb=80 Irb=10 Rbm=0 RE=25
             Rc=150 Xtb=1.5 Eg=1.20 Xti=2.5 Cje=95f Vje=0.67 Mje=0.34
             Tf=90p Cjc=387f Vjc=0.70 Mjc=0.40 Xcjc=0.3 Tr=1n Cjs=0.60p
             Vjs=0.52 Mjs=0.31)
```

CONTENTS